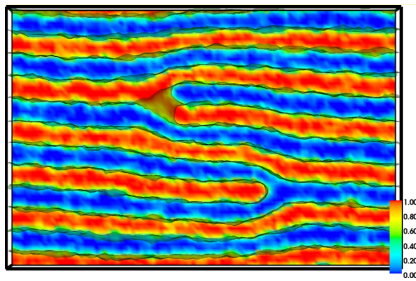


Thermodynamics and kinetics of defect motion and annihilation in the self-assembly of lamellar diblock copolymers

Marcus Müller

outline:

- models and techniques
- defect motion – dislocation glide and climb
- defect annihilation mechanisms



collaborators:

Weihua Li, Ulrich Welling, Juan C. Orozco Rey,
Su-Mi Hur, Abelardo Ramirez-Hernandez,
Paul F. Nealey, Juan J. de Pablo



CoLiSA.MMP



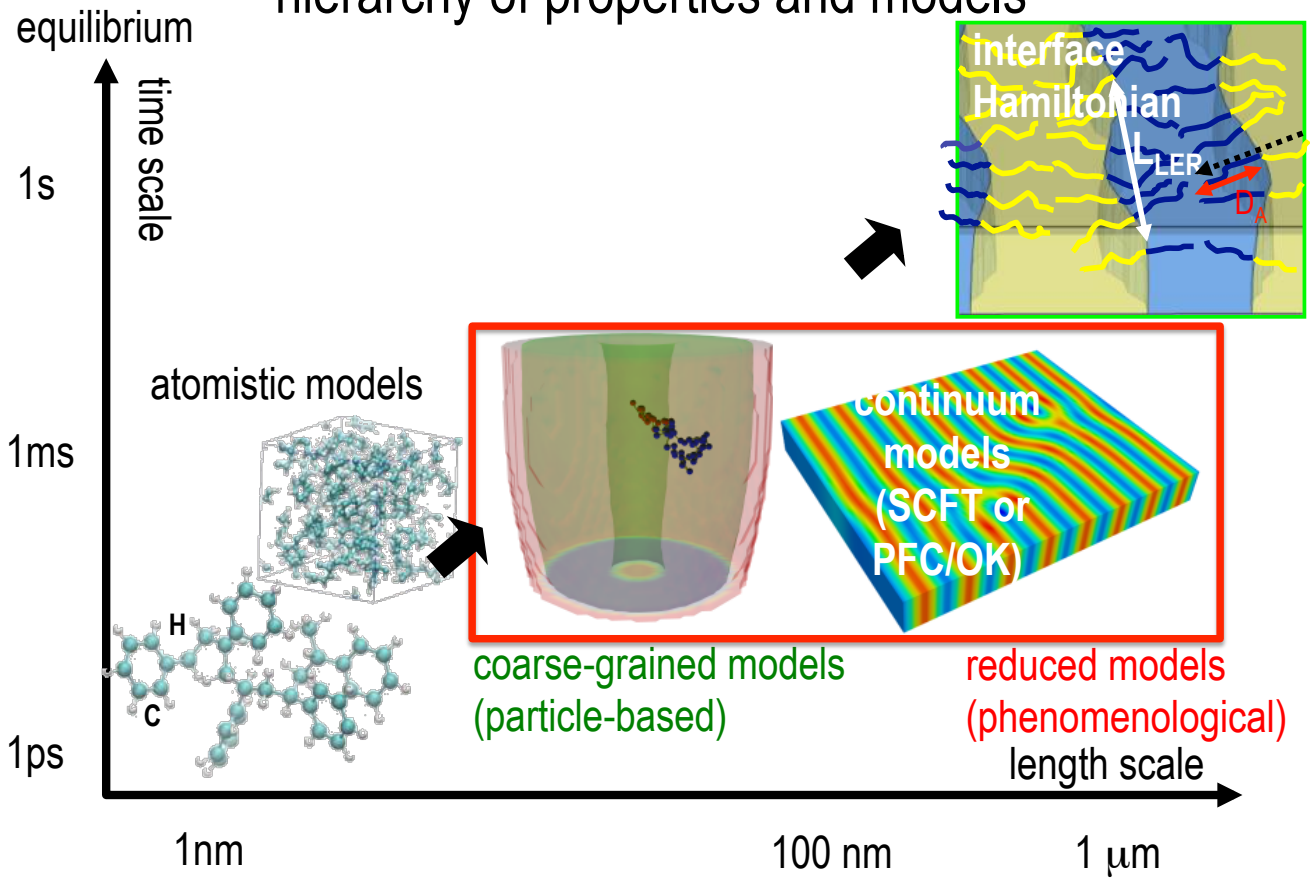
GEORG-AUGUST-UNIVERSITÄT
GÖTTINGEN

Li, Müller, *Annual Rev. Chem. Biomol. Eng.* **6**, 187 (2015)

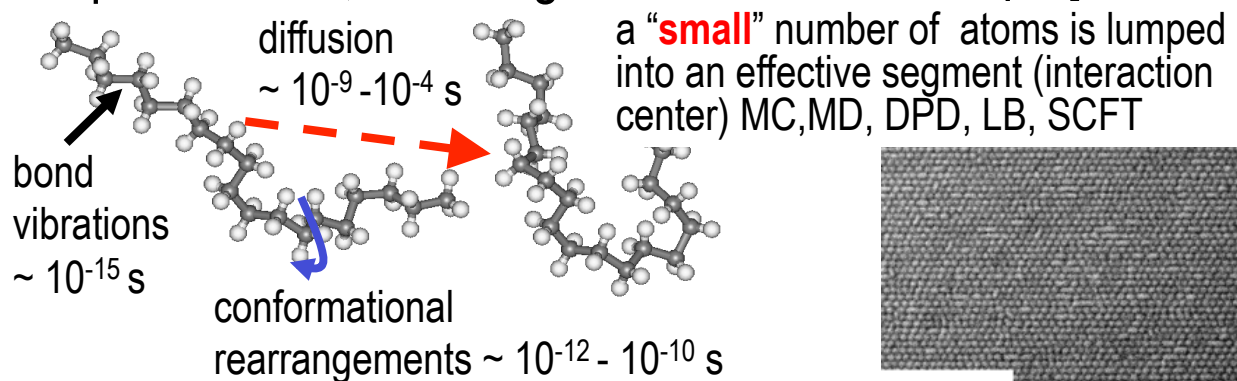
Li, Müller, *Prog. Polym. Sci.* **54–55**, 47 (2016)

UBC, Vancouver, August 1, 2017

hierarchy of properties and models



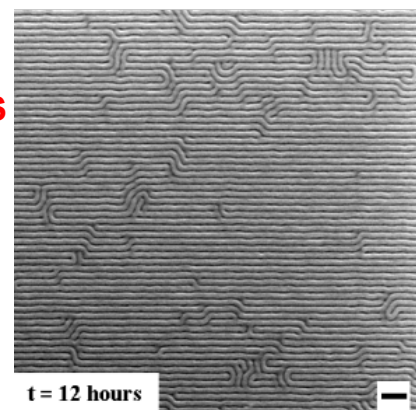
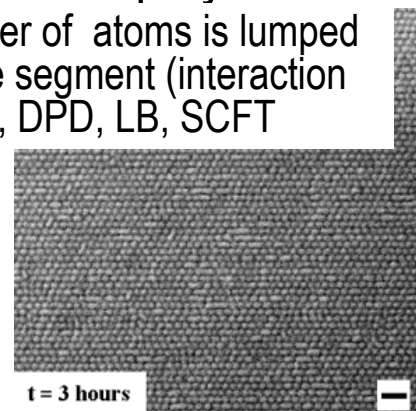
top-down soft, coarse-grained models for copolymers



minimal coarse-grained model that captures only **relevant interactions: connectivity, excl. volume, repulsion of unlike segments**

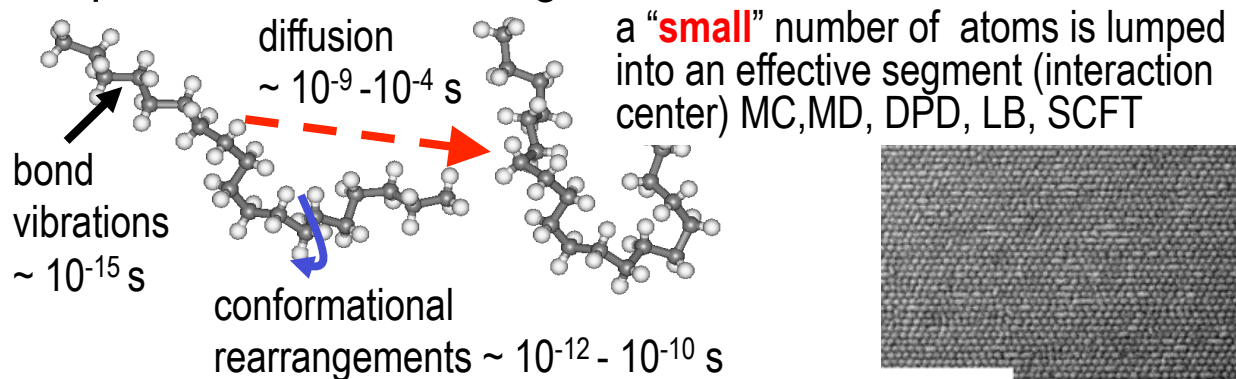
- incorporate essential interactions through a small number of effective parameters: chain extension, R_e , compressibility κN and Flory-Huggins parameter $\chi N \rightarrow$ **universality**
- elimination of degrees of freedom

→ soft interactions



Daoulas, Müller, JCP 125, 184904 (2006)

top-down soft, coarse-grained models for copolymers

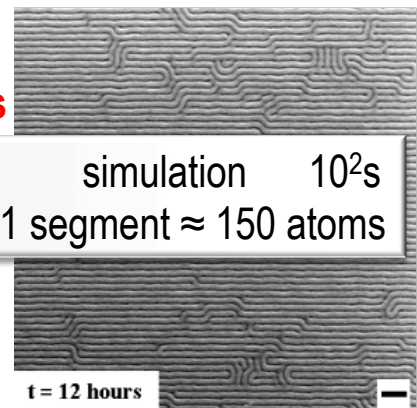
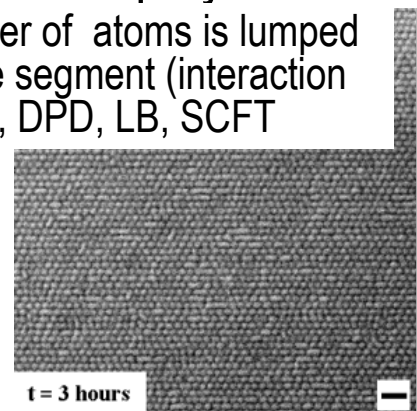


minimal coarse-grained model that captures only **relevant interactions: connectivity, excl. volume, repulsion of unlike segments**

10^{-15} s minimal, soft, coarse-grained model 10^{-5} s
 1 polymer \approx 5000 (heavy) atoms \approx 32 segments
 chain extension, R_e , compressibility K_N and
 Flory-Huggins parameter $\chi N \rightarrow$ **universality**

- elimination of degrees of freedom

→ soft interactions



Daoulas, Müller, JCP 125, 184904 (2006)

minimal, soft, coarse-grained models

bead-spring model with soft, pairwise interactions

$$\frac{\mathcal{H}_b[\mathbf{r}_i(s)]}{k_B T} = \sum_{s=1}^{N-1} \frac{3(N-1)}{2R_{eo}^2} [\mathbf{r}_i(s) - \mathbf{r}_i(s+1)]^2$$

molecular architecture:
Gaussian chain

$$\frac{\mathcal{H}_{ord}[\hat{\phi}_A, \hat{\phi}_B]}{k_B T \sqrt{\bar{N}}} = -\frac{\chi_o N}{4} \int \frac{d^3 \mathbf{r}}{R_{eo}^3} [\hat{\phi}_A(\mathbf{r}) - \hat{\phi}_B(\mathbf{r})]^2$$

with $\sqrt{\bar{N}} \equiv \Phi_p R_{eo}^3$

$$\frac{\mathcal{H}_{melt}[\hat{\phi}_A, \hat{\phi}_B]}{k_B T \sqrt{\bar{N}}} = +\frac{\kappa_o N}{2} \int \frac{d^3 \mathbf{r}}{R_{eo}^3} [\hat{\phi}_A(\mathbf{r}) + \hat{\phi}_B(\mathbf{r}) - 1]^2$$

effective interactions become weaker for large degree of coarse-graining

➡ no (strict) excluded volume, soft, effective segments can overlap,
rather enforce low compressibility on length scale of interest, R_{eo}

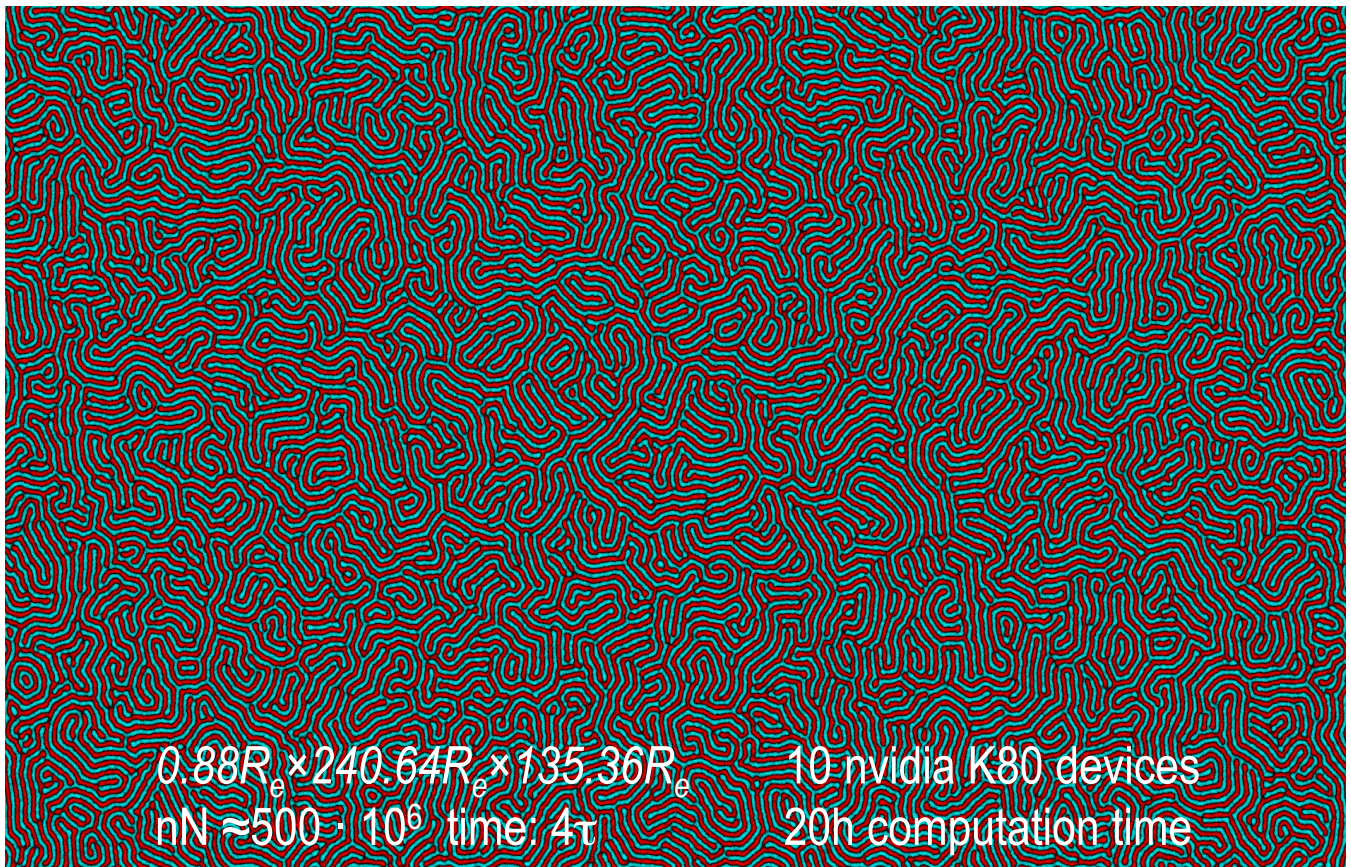
“ $\hat{\phi}_A(\mathbf{r}) = \frac{1}{\rho_o} \sum_{i_A=1}^{nNf} \delta(\mathbf{r} - \mathbf{r}_{i_A})$ ” $\hat{\phi}^2$ -terms generate pairwise interactions
particle-based description for MC, BD, DPD,
or SCMF simulations

Müller, Smith, J. Polym. Sci. B **43**, 934 (2005); Daoulas, Müller, JCP **125**, 184904 (2006); Detcheverry, Kang, Daoulas, Müller, Nealey, de Pablo, Macromolecules **41**, 4989 (2008); Pike, Detcheverry, Müller, de Pablo, JCP **131**, 084903 (2009); Detcheverry, Pike, Nealey, Müller, de Pablo, PRL **102**, 197801 (2009)

top-down soft, coarse-grained models for copolymers

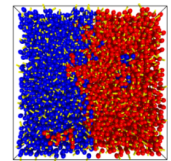


top-down soft, coarse-grained models for copolymers



particle simulation and continuum description

system: symmetric AB copolymer



degrees of freedom:

particle coordinates, $N(n_A + n_B)$
 $\{\mathbf{r}_i(s)\}$

composition field (and density), ∞

$$m(\mathbf{r}) = \phi_A(\mathbf{r}) - \phi_B(\mathbf{r})$$

$$\rho(\mathbf{r}) = \phi_A(\mathbf{r}) + \phi_B(\mathbf{r}) \approx \rho_0$$

model definition:

intra- and intermolecular potentials
 (here: soft, coarse-grained model, SCMF)
 single-chain dynamics
 (here: Rouse dynamics)
 segmental friction, ζ

free-energy functional, $\mathcal{F}_{\text{GL}}[m(\mathbf{r})]$
 (Ginzburg-Landau-de Gennes or Ohta-Kawasaki)
 time-dependent GL theory
 (model B according to Hohenberg & Halperin)
 Onsager coefficient, $\Lambda(\mathbf{r} - \mathbf{r}')$

projection:

$$\hat{\phi}_A(\mathbf{r}) \equiv \frac{1}{\rho_0} \sum_{i=1}^{n_A} \sum_{s=1}^N \delta(\mathbf{r} - \mathbf{r}_i(s))$$

$$\frac{\mathcal{F}[m]}{k_B T} \equiv - \ln \int \mathcal{D}\{\mathbf{r}_{i,s}\} e^{-\frac{\mathcal{H}(\{\mathbf{r}_{i,s}\})}{k_B T}} \delta[m - (\hat{\phi}_A - \hat{\phi}_B)] \longrightarrow \mathcal{Z} \sim \int \mathcal{D}[m] e^{-\frac{\mathcal{F}[m]}{k_B T}}$$

$$\Lambda(\mathbf{r} - \mathbf{r}') = \left\langle \frac{\partial \hat{\phi}(\mathbf{r})}{\partial \mathbf{r}_i(s)} M_{\zeta, i, j}(s, t) \frac{\partial \hat{\phi}(\mathbf{r}')}{\partial \mathbf{r}_j(t)} \right\rangle$$

Kawasaki, Sekimoto, Physica 143A, 349 (1987)

speed-up particle simulations by concurrent coupling

question: why are particle simulations slow?

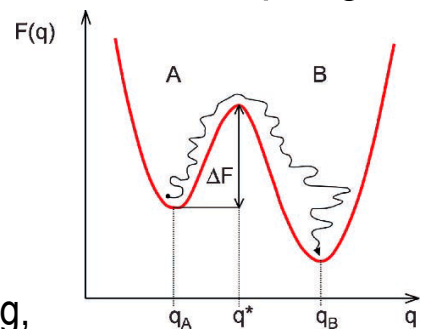
1) **barrier problem (b):**

system has to overcome a **free-energy barrier**,

Kramer's theory $\tau \sim \exp(-\Delta F/k_B T)$

solutions: WL sampling, conf.T-WL, conf. flooding,

metadynamics, transition-path sampling, forward flux sampling, ...



Dellago, Bolhuis, Adv. Polym. Sci **221**, 167 (2008)

2) **time-scale problem (a): “intrinsically slow processes”**

downhill in continuum free energy but **small Onsager coefficient** (response to TD force) and/or two **vastly different time scales** (stiff equations)

stiff interaction dictates time step, weak interaction drives slow time evolution

solutions: •reversible multiple time step MD (RESPA)

Tuckerman, Berne, Martyna, JCP **97**, 1990 (1992)

•SCMF simulation

Müller, Smith J.Polym.Sci.B **43**, 934 (2005)

•HMM

E, Engquist, Li, Ren, Vanden-Eijnden, Comm. Comp. Phys. **2**, 367 (2007)

free-energy functional from restraint simulations

idea: restrain the composition, $\hat{m} \equiv \hat{\phi}_A - \hat{\phi}_B$, of particle model to fluctuate around the order-parameter field, $m(\mathbf{r})$, of the continuum description (**field-theoretic umbrella sampling** for order-parameter field, $m(\mathbf{r})$)

$$\frac{\mathcal{H}_b[\mathbf{r}_i(s)]}{k_B T} = \sum_{s=1}^{N-1} \frac{3(N-1)}{2R_{eo}^2} [\mathbf{r}_i(s) - \mathbf{r}_i(s+1)]^2 \quad \text{bead-spring model}$$

$$\frac{\mathcal{H}_{nb}[\hat{\phi}_A, \hat{\phi}_B]}{k_B T \sqrt{N}} = \int \frac{d^3 \mathbf{r}}{R_{eo}^3} \left(\frac{\kappa_o N}{2} [\hat{\phi}_A + \hat{\phi}_B - 1]^2 - \frac{\chi_o N}{4} [\hat{\phi}_A - \hat{\phi}_B]^2 \right) \quad \text{soft, non-bonded}$$

$$\frac{\mathcal{H}_{\lambda N}}{k_B T \sqrt{N}} = \frac{\lambda N}{2} \int \frac{d^3 \mathbf{r}}{R_{eo}^3} \left\{ \left[\hat{\phi}_A - \frac{1+m}{2} \right]^2 + \left[\hat{\phi}_B - \frac{1-m}{2} \right]^2 \right\} \quad \text{restrain composition}$$

$\lambda N \gg \chi_o N$ strong coupling between particle model and continuum description

$$\exp \left(-\frac{\mathcal{H}_{\lambda N}}{k_B T} \right) \xrightarrow{\lambda N \rightarrow \infty} \delta \left(m(\mathbf{r}) - \hat{\phi}_A + \hat{\phi}_B \right) \delta \left(\hat{\phi}_A + \hat{\phi}_B - 1 \right)$$

$$\mu(\mathbf{r}) = \frac{\delta \mathcal{F}}{\delta m(\mathbf{r})} \xrightarrow{\lambda N \rightarrow \infty} \frac{\delta \mathcal{F}_{\lambda N}}{\delta m(\mathbf{r})} = \left\langle \frac{\delta \mathcal{H}_{\lambda N}}{\delta m(\mathbf{r})} \right\rangle$$

$$\mu^* \equiv \frac{\mu R_{eo}^3}{k_B T \sqrt{N}} \xrightarrow{\lambda N \rightarrow \infty} \frac{\lambda N}{2} \left(m(\mathbf{r}) - \langle \hat{\phi}_A(\mathbf{r}) - \hat{\phi}_B(\mathbf{r}) \rangle \right) = \frac{\lambda N}{2} \left(m(\mathbf{r}) - \langle \hat{m}(\mathbf{r}) \rangle \right)$$

inspired by Maragliano, Vanden-Eijnden, *Chem. Phys. Lett.* **426**, 168 (2006)
Müller, Daoulas, *Phys. Rev. Lett.* **107**, 227801 (2011)

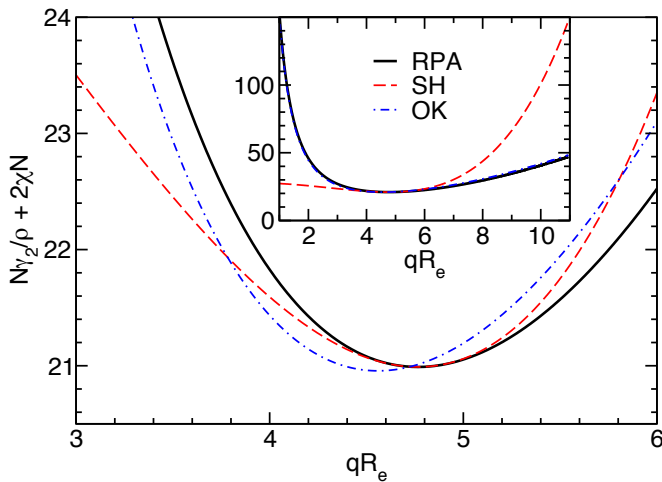
continuum models

Self-Consistent-Field Theory (SCFT) [classical DFT for copolymers/MFA]
 Leibler's RPA: systematic expansion in order parameter $\Psi = \phi_A - f$

$$\frac{\mathcal{F}[\Psi]}{k_B T} = +\frac{1}{2!} \int \frac{d\mathbf{q}}{(2\pi)^3} \gamma_2(\mathbf{q}) \Psi_{\mathbf{q}} \Psi_{-\mathbf{q}} + \frac{1}{3!} \int \frac{d\mathbf{q}_1 d\mathbf{q}_2}{(2\pi)^6} \gamma_3(\mathbf{q}_1, \mathbf{q}_2) \Psi_{\mathbf{q}_1} \Psi_{\mathbf{q}_2} \Psi_{-\mathbf{q}_1-\mathbf{q}_2}$$

0 for symmetric copolymers, $f=1/2$

$$+ \frac{1}{4!} \int \frac{d\mathbf{q}_1 d\mathbf{q}_2 d\mathbf{q}_3}{(2\pi)^9} \gamma_4(\mathbf{q}_1, \mathbf{q}_2, \mathbf{q}_3) \Psi_{\mathbf{q}_1} \Psi_{\mathbf{q}_2} \Psi_{\mathbf{q}_3} \Psi_{-\mathbf{q}_1-\mathbf{q}_2-\mathbf{q}_3}$$



PFC / Swift-Hohenberg model

$$\frac{N}{\rho} \gamma_{2\text{-SH}}(q) = \tau_0 + \varepsilon_0 \left[(q^* R_e)^2 - (q R_e)^2 \right]^2$$

Ohta-Kawasaki model

$$\frac{N}{\rho} \gamma_{2\text{-OK}}(q) = \frac{(q R_e)^2}{3} + 7.1 - 2\chi N + \frac{144}{(q R_e)^2}$$

continuum models

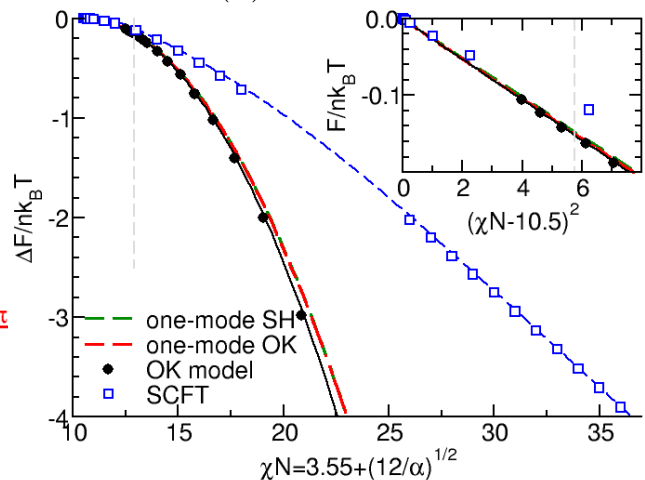
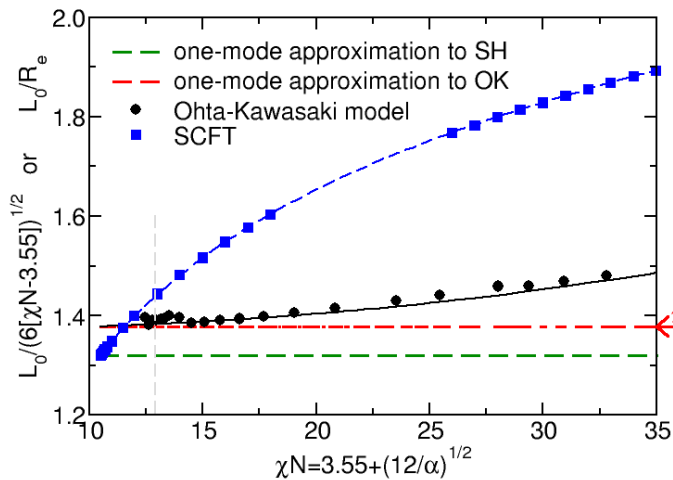
PFC / Swift-Hohenberg model

$$\mathcal{F}_{\text{SH}}[m] = \int d\mathbf{x} \left(\frac{1}{2} m \left\{ -\tilde{\epsilon} + [1 + \Delta]^2 \right\} m + \frac{1}{4} m^4 \right)$$

Ohta-Kawasaki model

$$\mathcal{F}_{\text{OK}}[m] = \int d\mathbf{x} \left(\frac{1}{2} m \left\{ -\Delta - 1 + \tilde{\alpha} \int d\mathbf{x}' G(\mathbf{x}, \mathbf{x}') \right\} m + \frac{1}{4} m^4 \right)$$

conserved dynamics (model B) $\frac{\partial m}{\partial t} = -\nabla \mathbf{j} = \Lambda \Delta \frac{\delta \mathcal{F}}{\delta m(\mathbf{x})}$



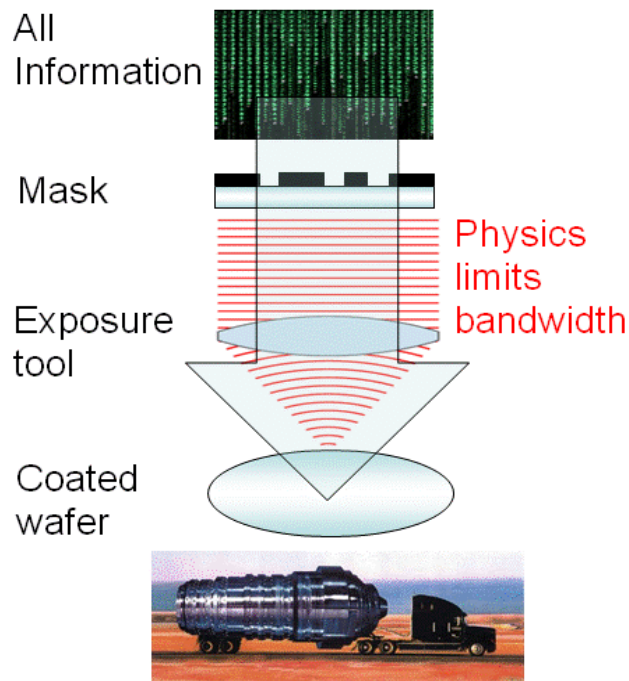
continuum models

PFC / Swift-Hohenberg model *versus* Ohta-Kawasaki model

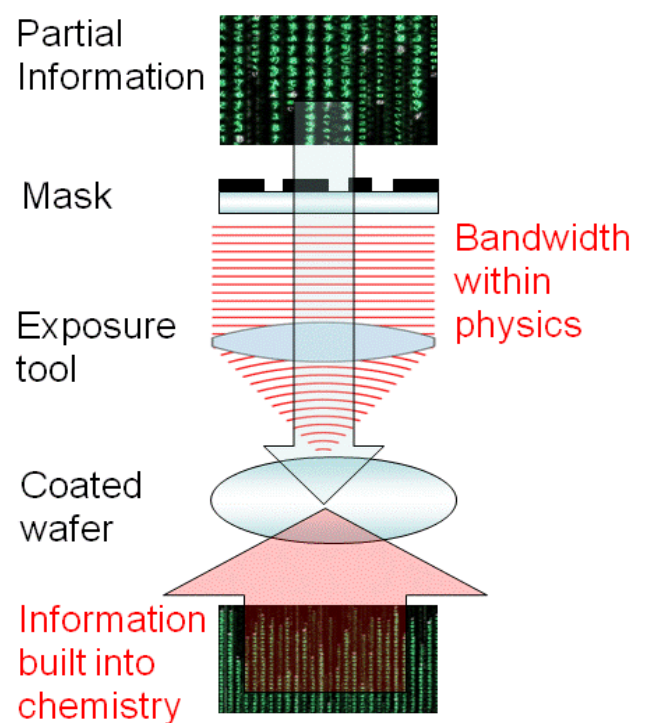
- | | |
|---|--|
| + no long-range part in free-energy | - long-range (Coulomb) contribution to free energy [but model B dynamics with local Onsager coefficient is not long-ranged] |
| - higher-order spatial derivative | |
| - predicts macrophase separation between spatially modulated phases (and disordered structures) for asymmetric compositions | + qualitative agreement with phase diagram |
| - tight dislocation pairs are unstable in relevant parameter range | + tight dislocation pairs exhibit transition from unstable to metastable at intermediate segregation |

copolymer lithography: directed assembly of copolymers into nanostructures

Top Down Lithography



Bottom Up Lithography

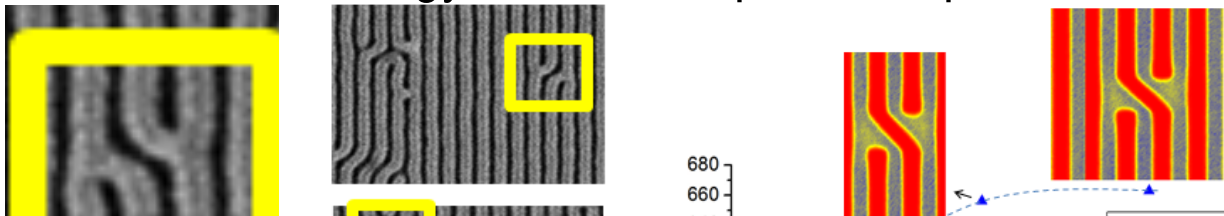


courtesy of Ralph Dammel

http://www.nikonprecision.com/ereview/spring_2013/images/featured-4L.gif

LithoVision | 2013

defect free energy for lamellar pattern replication

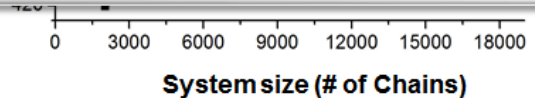


defects observed in experiments are not thermal fluctuations around an ordered equilibrium state but appear in the course of structure formation



tailor the kinetics of structure formation to
(a) avoid defect formation and (b) facilitate defect annihilation

process-directed self-assembly



naïve estimate:

$$\Delta F = \gamma A \approx \frac{\sqrt{N} k_B T}{Re_o^2} \times 2L_s D_o$$

$$\approx 128 k_B T \times 3.6 = 460 k_B T$$

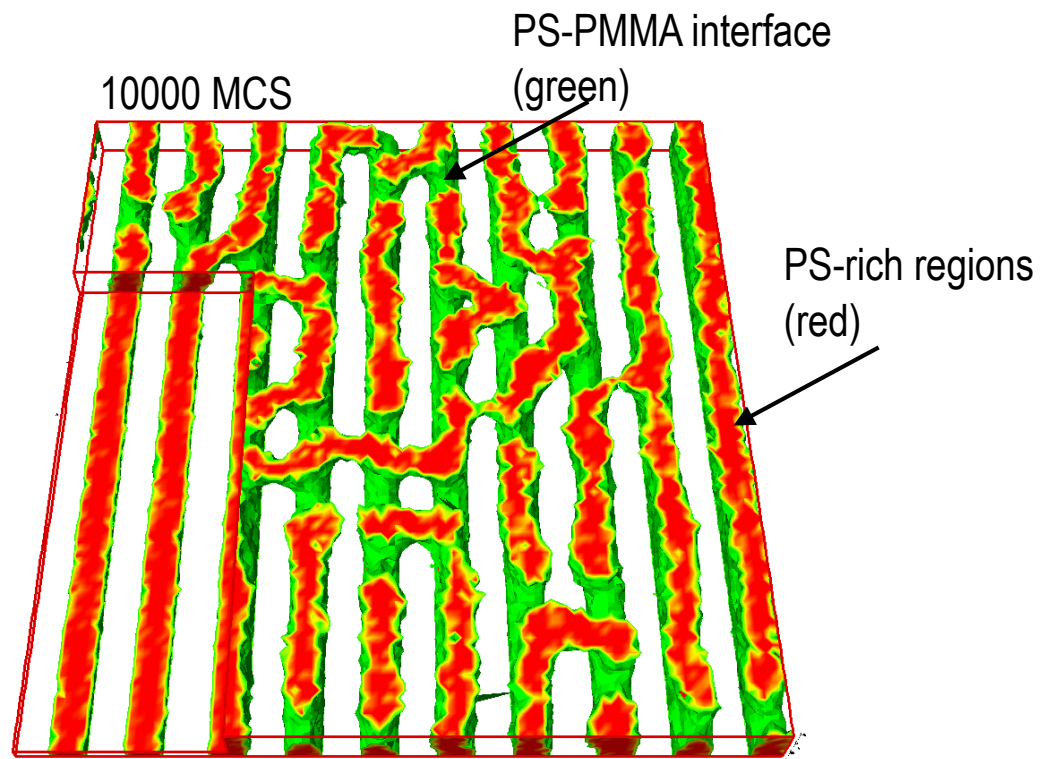


extremely small defect density in equilibrium

$$\Delta F_d = 30 k_B T \rightarrow \sigma_d \sim 0.001 / \text{cm}^2$$

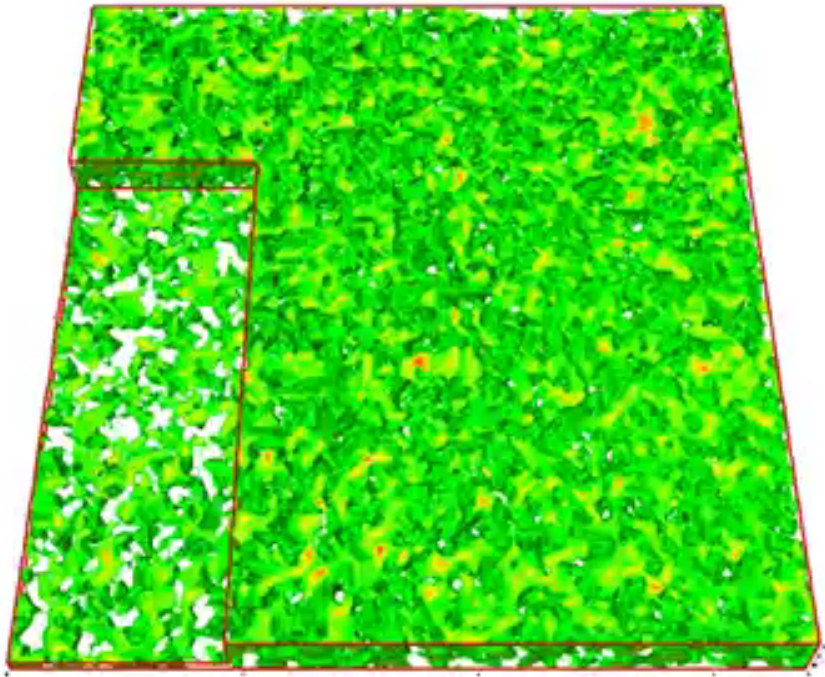
Nagpal, Müller, Nealey, de Pablo, *ACS Macro Letters* 1, 418 (2012)

ordering kinetics: SCMF simulations

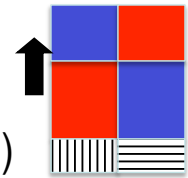


Edwards, Stokovich, Müller, Solak, de Pablo, Nealey, *J. Polym. Sci B* 43, 3444 (2005)

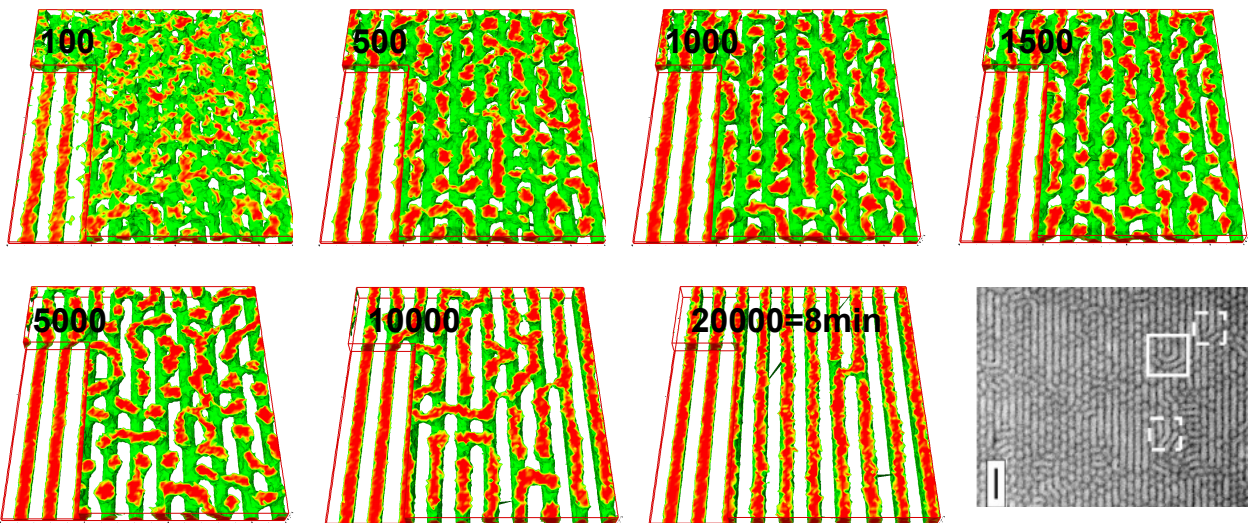
ordering kinetics: SCMF simulations



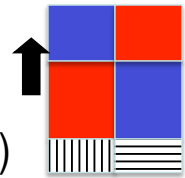
ordering kinetics: SCMF simulations



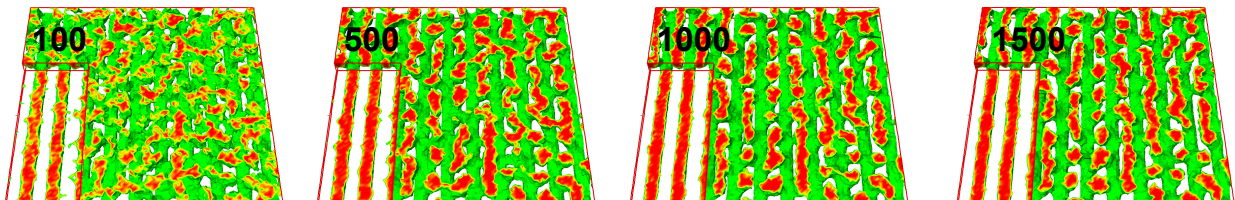
- 1) surface pattern directs spinodal self-assembly into a checkerboard pattern (bottom registered, top anti-registered)
 - 2) interface between registered and anti-registered grain shifts upwards and the anti-registered grain become thinner and breaks up (dots)
- ➔ perfect order is established by **perpendicular interface movement** (instead of lateral defect motion and annihilation)



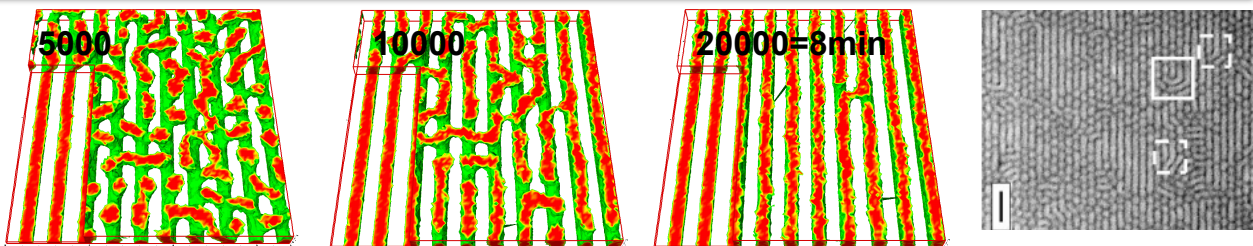
ordering kinetics: SCMF simulations



- 1) surface pattern directs spinodal self-assembly into a checkerboard pattern (bottom registered, top anti-registered)
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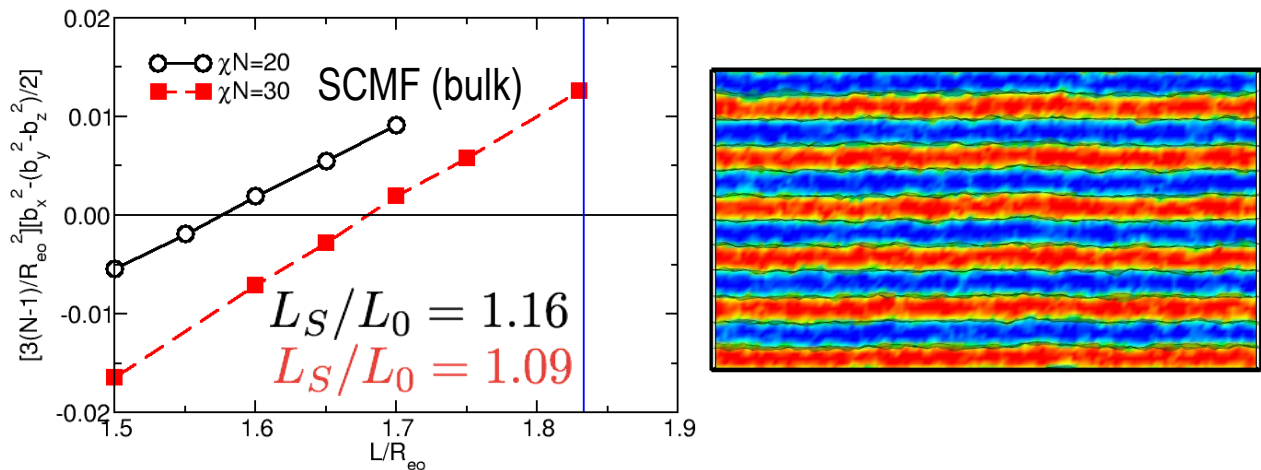
defect removal = wetting of the aligned, registered grain



process-directed self-assembly

SCMF simulation of DSA under non-optimal conditions:

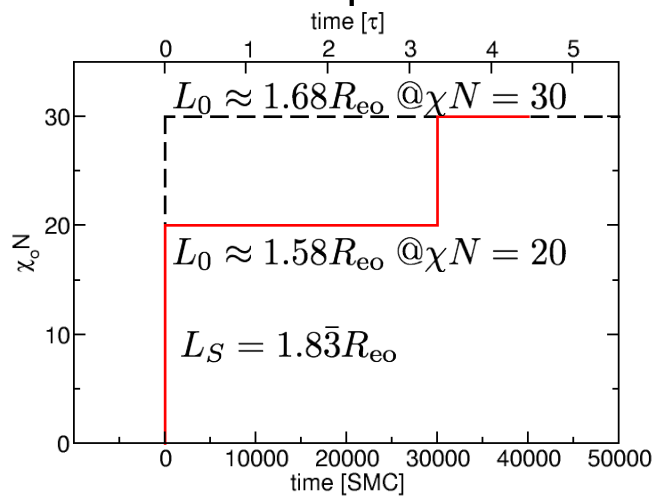
weak surface interaction $\Lambda N = 0.1$ and period mismatch $L_S = 1.8\bar{3}R_{eo}$



high incompatibility: $L_0 \approx 1.68R_{eo}$ @ $\chi N = 30$ small mismatch

low incompatibility: $L_0 \approx 1.58R_{eo}$ @ $\chi N = 20$ large mismatch

process-directed self-assembly



process-directed self-assembly:

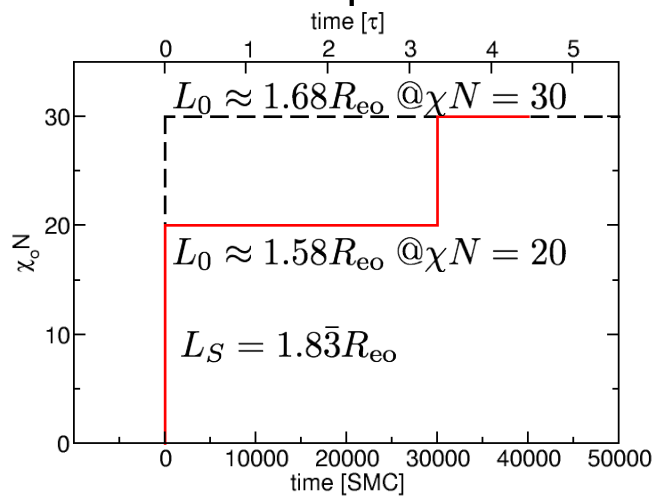
1) one-step quench:

$$\chi_0 N = 0 \rightarrow 30$$

2) two-step quench:

$$\chi_0 N = 0 \rightarrow 20 \rightarrow 30$$

process-directed self-assembly



process-directed self-assembly:

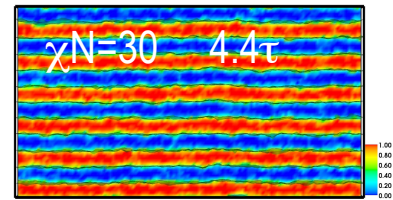
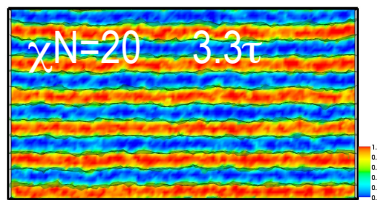
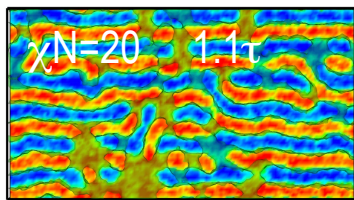
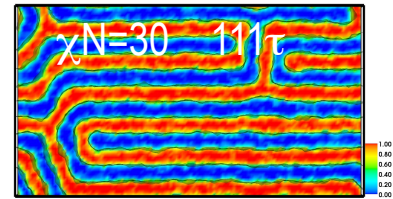
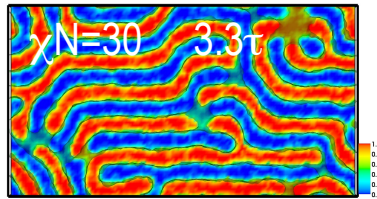
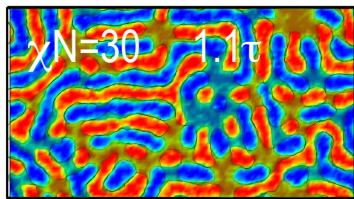
1) one-step quench:

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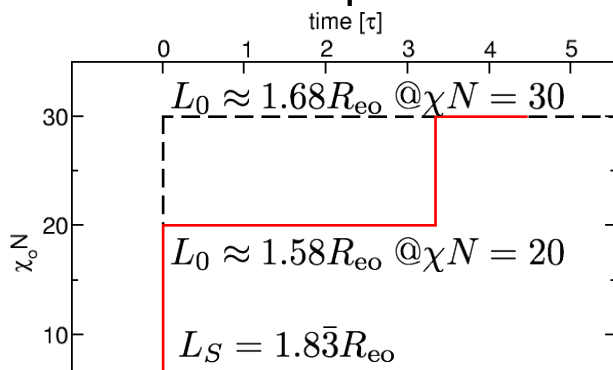
2) two-step quench:

$$\chi_0 N = 0 \rightarrow 20 \rightarrow 30$$

➔ observation: two-step quench results in pattern replication although ...



process-directed self-assembly



process-directed self-assembly:

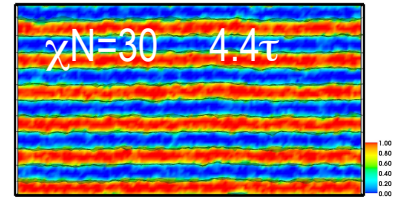
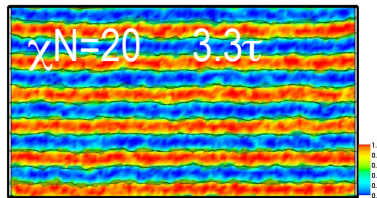
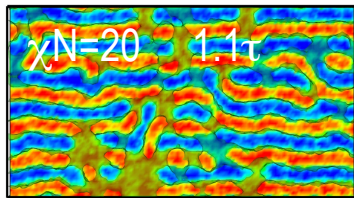
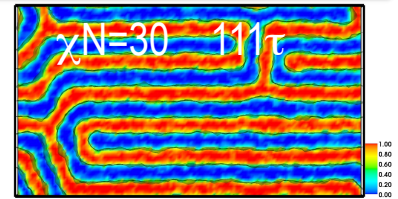
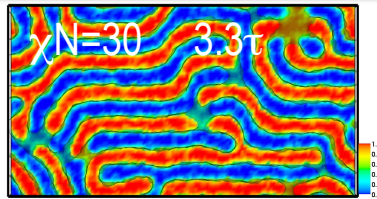
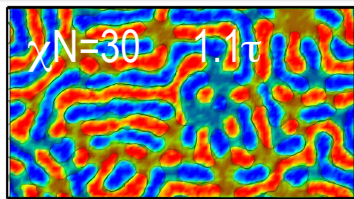
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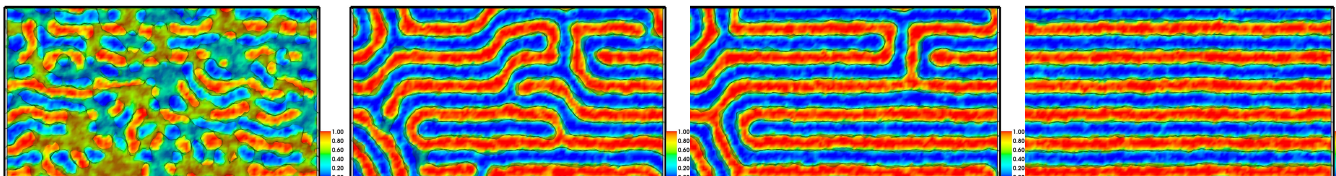
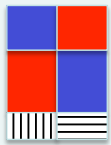
$$\chi_0 N = 0 \rightarrow 20 \rightarrow 30$$

why does the two-step process that gives rise to a “worse” match between the guiding pattern and the equilibrium structure yields defect-free self-assembly?

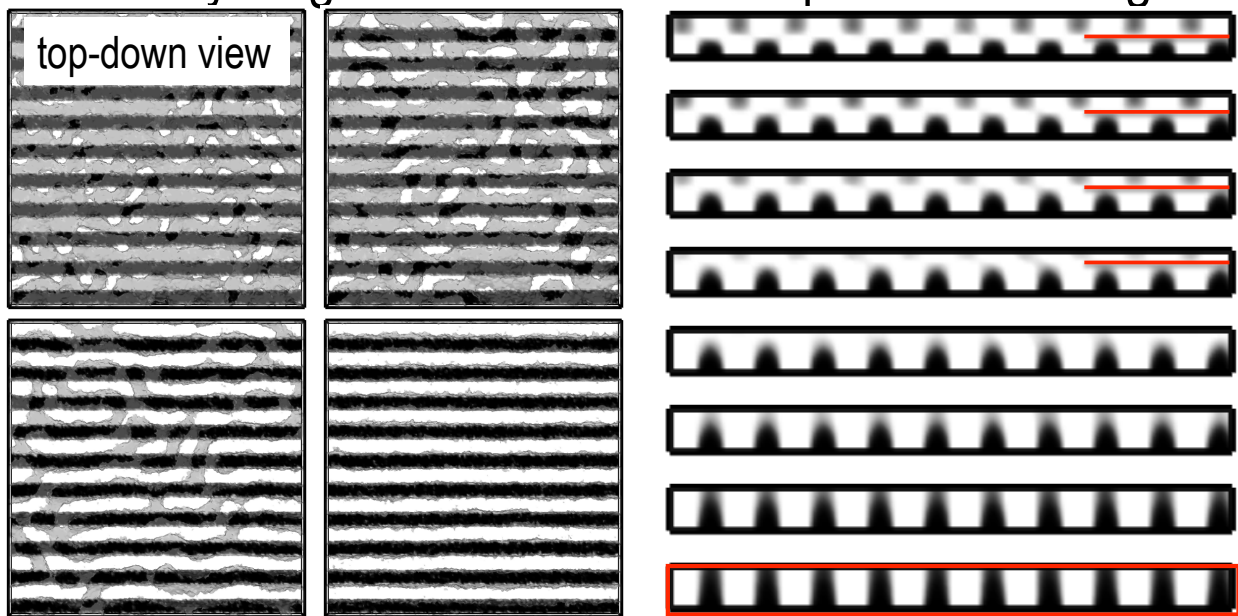


kinetics of structure formation: thin-film *versus* directed self-assembly

	thin-film self-assembly	directed self-assembly (DSA)
spinodal self-assembly: fingerprint pattern $\tau = R_{e0}^2 / D$	spontaneous growth of (most) instable mode	guiding fields direct spinodal structure formation
local defect annihilation and grain formation	<i>defects move in response to strain-field mediated interactions, defects collide and annihilate</i>	
late stage: grain coarsening	universal power-law behavior of grain growth, grain boundary motion	defect-free assembly already achieved because guiding fields dictate grain orientation and registration



early stages: surface-directed spinodal ordering



$t = 1000, 3000, 8000, 14000$ SMC

$\tau = R_{e0}^2/D = 8990$ SMC (≈ 1 min)

$t = 1000, 2000, 3000, 4000, 5000,$
 $6000, 8000, 10000$ SMC

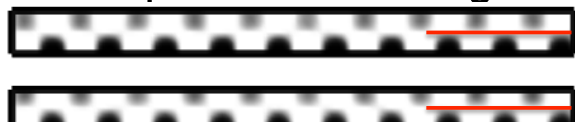
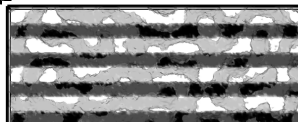
$\chi N = 30$, 1:1 pattern replication, symmetric stripe pattern $W/L_0 = 1/2$, $\Delta N = \pm 2$

➡ rapid, defect-free pattern replication via formation of checkerboard pattern

Müller, Li, Orozco Rey, Welling, *J. Phys.: Conf. Ser.* **640**, 012010 (2015)

early stages: surface-directed spinodal ordering

top-down view



initial stage – homogeneously mixed disordered system – is unstable and spontaneously microphase separates

three processes:

- chemical guiding pattern induces structure formation (linear growth in time)

$$\frac{\partial \phi_A(\mathbf{q}, t)}{\partial t} \sim h(\mathbf{q})$$

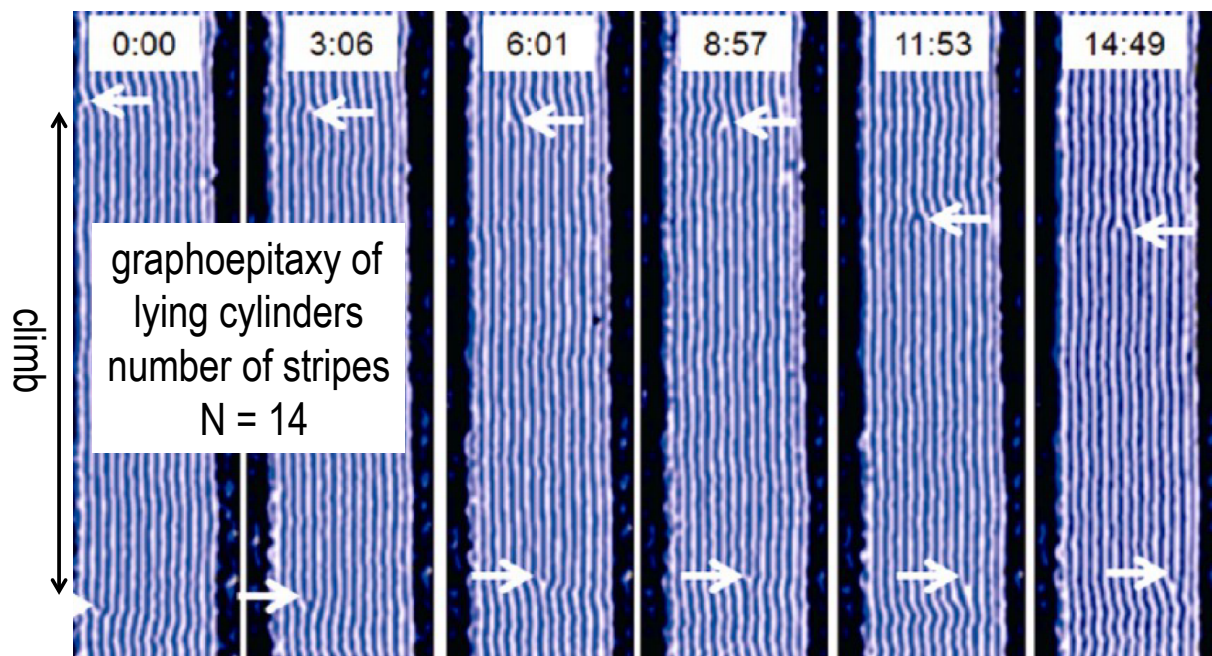
with $h(\mathbf{q})$ being the Fourier transform of chemical pattern

- spontaneous growth of composition fluctuations in initial stage (exponential growth in time) \Rightarrow checkerboard structure
- film consists of registered bottom and shifted top grain interface (grain boundary) moves to top of film

\Rightarrow rapid, defect-free pattern replication via formation of checkerboard pattern

Müller, Li, Orozco Rey, Welling, *J. Phys.: Conf. Ser.* **640**, 012010 (2015)

dislocation climb – no barrier for motion parallel to stripes



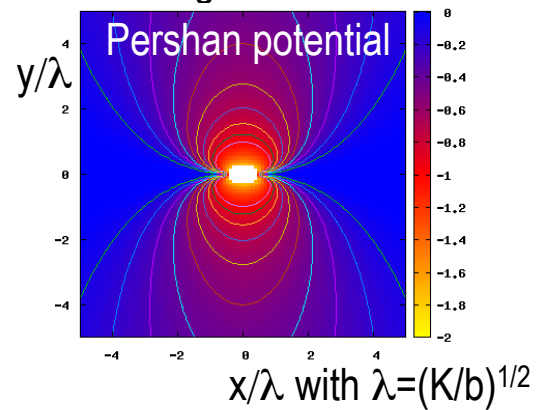
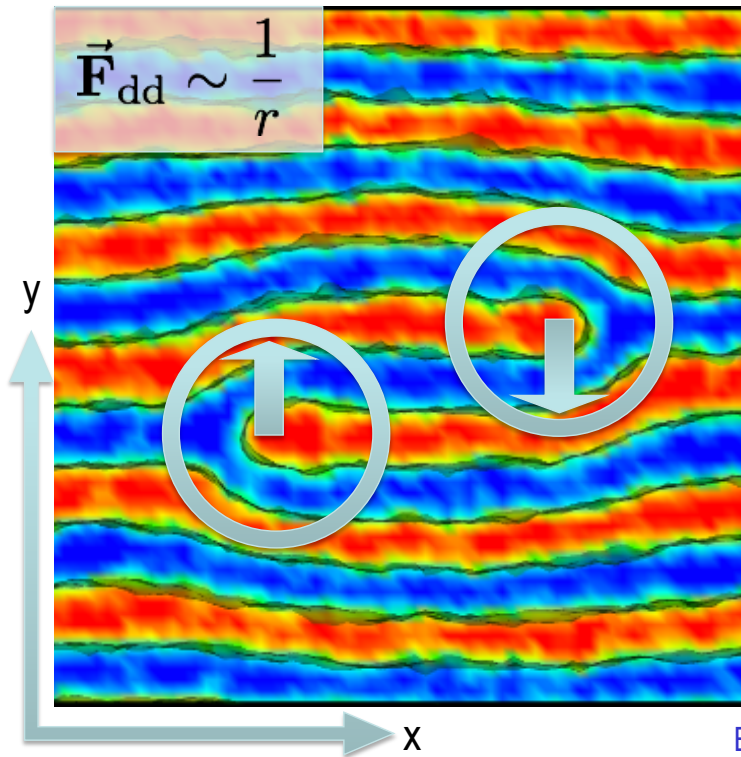
attractive force between edge dislocations with opposite Burgers vectors
 Peach-Koehler force $\sim -c/L$, overdamped motion: velocity $\sim \nu c/L$

➡ $L^2(t) = a - Dt$ with $D = 2\nu c$

Tong, Sibener, *Macromolecules* **46**, 8538 (2013)

dislocation motion – glide and climb

system: dislocation pair, $\chi N=30$, non-patterned surface
particle simulations using Single-Chain-in-Mean-Field algorithm



strain-field mediated attraction
between edge dislocations with
opposite Burgers vectors

➡ **Peach-Koehler force**

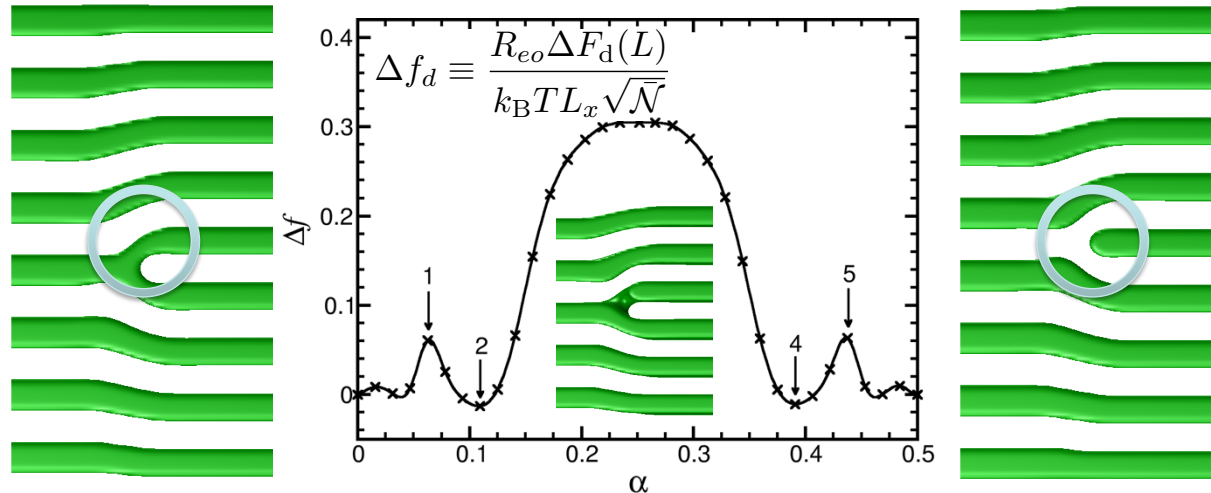
Peach, Koehler, *Phys. Rev.* **80**, 436 (1950)

Pershan, *J. Appl. Phys.* **45**, 1590 (1974)

Eykholt, Srolovitz, *J. Appl. Phys.* **65**, 4204 (1989)

dislocation glide – barrier for motion perpendicular to stripes

system: dislocation glide by half a period, $\chi N=30$, non-patterned surface
self-consistent field theory (SCFT) calculations / string method F[W]



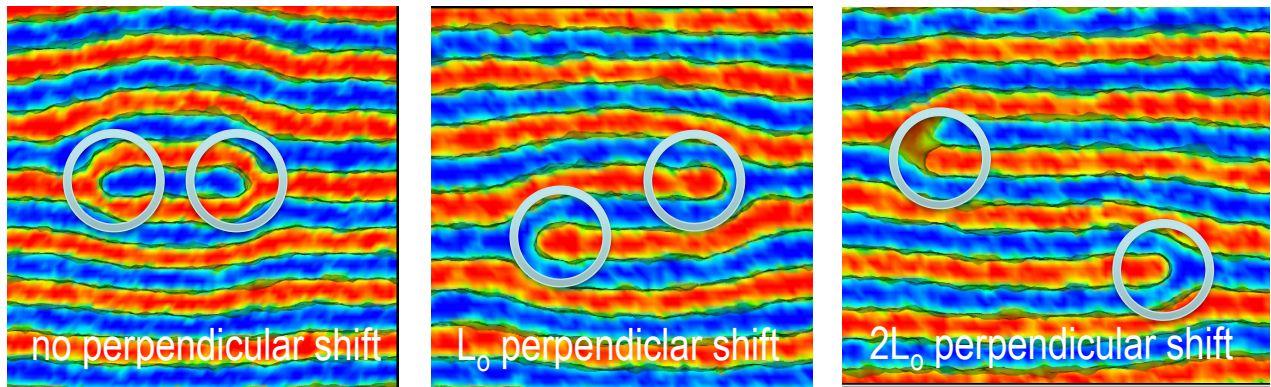
defect motion perpendicular to stripes involves domain breaking (barrier)

- very low defect mobility for perpendicular glide motion
- perpendicular distance between edge dislocations remains conserved
- translation invariance along stripes \Rightarrow **no barrier for climb motion**

Li, Müller, *Macromolecules* **49**, 6126 (2016)

dislocation climb: which defect annihilates first?

system: dislocation pair, $\chi N=30$, no pattern, different “**impact parameters**”
particle simulations using Single-Chain-in-Mean-Field algorithm



dislocation pair with opposite Burgers vectors (different perp. distances)

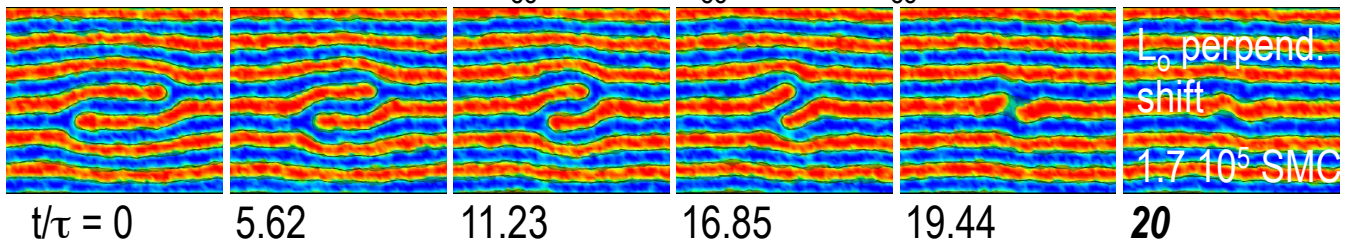
➡ attractive Peach-Koehler force results in defect motion parallel to stripes

questions:

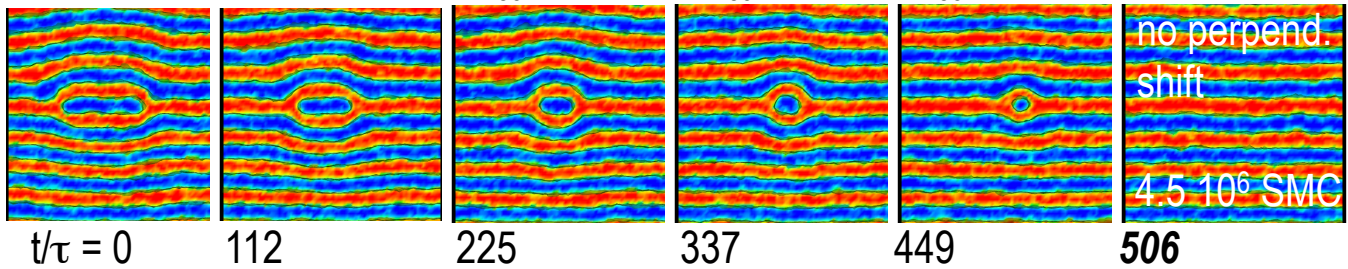
- how large is the attractive force?
- how fast does the defect move?
- does defect motion/collision result in defect annihilation?

dislocation climb

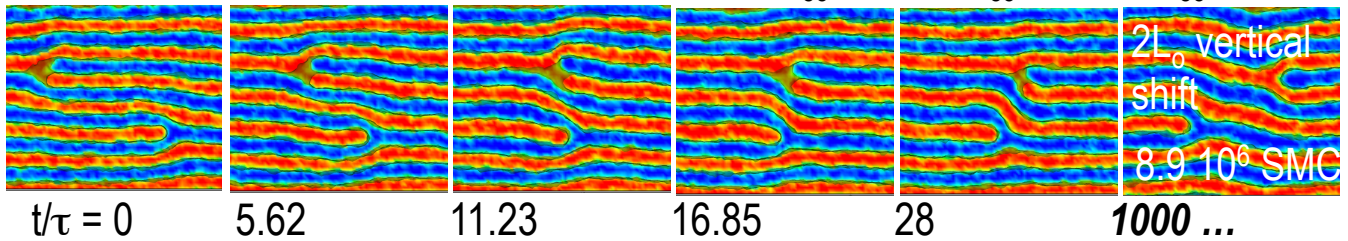
unconstraint climb: $1.26R_{e0} \times 22.67R_{e0} \times 10.07R_{e0}$



evaporation climb: $1.26R_{e0} \times 12.5925R_{e0} \times 25.185R_{e0}$

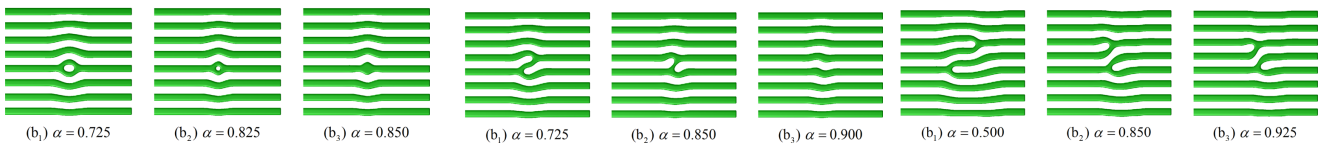
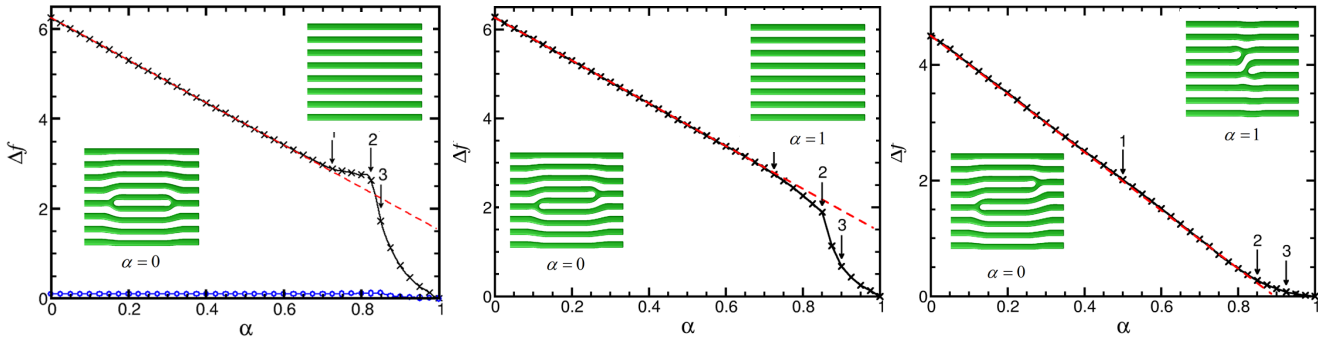


stagnation climb – metastable dipole: $1.26R_{e0} \times 15.11R_{e0} \times 10.07R_{e0}$



a) how large is the attractive force?

system: dislocation pair, $\chi N=30$, non-patterned surface
 SCFT calculations, string method $F[W]$



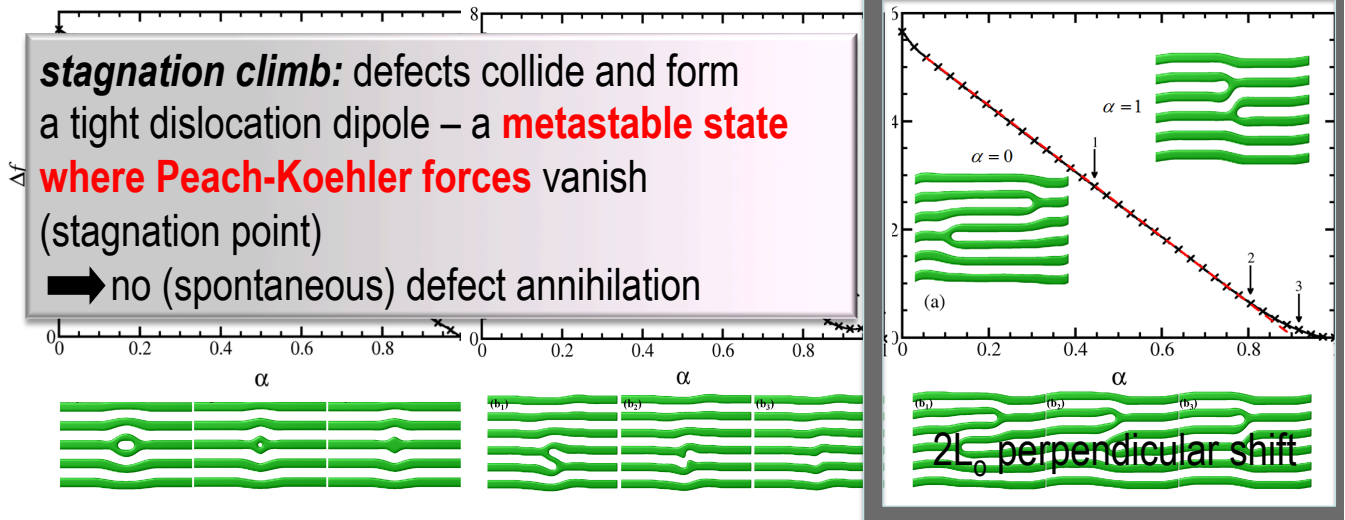
excess free energy depends linearly on distance L (parallel to stripes)
 thermodynamic driving force: excess free energy of extra half lamella

$$\Delta F_d \sim L \Rightarrow -\frac{\partial \Delta F_d}{\partial L} = \text{const} \quad \text{and } \mathbf{\text{same magnitude for all 3 cases}}$$

Li, Müller, *Macromolecules* **49**, 6126 (2016)

a) how large is the attractive force?

system: dislocation pair, $\chi N=30$, non-patterned surface
 SCFT calculations, string method $F[W]$



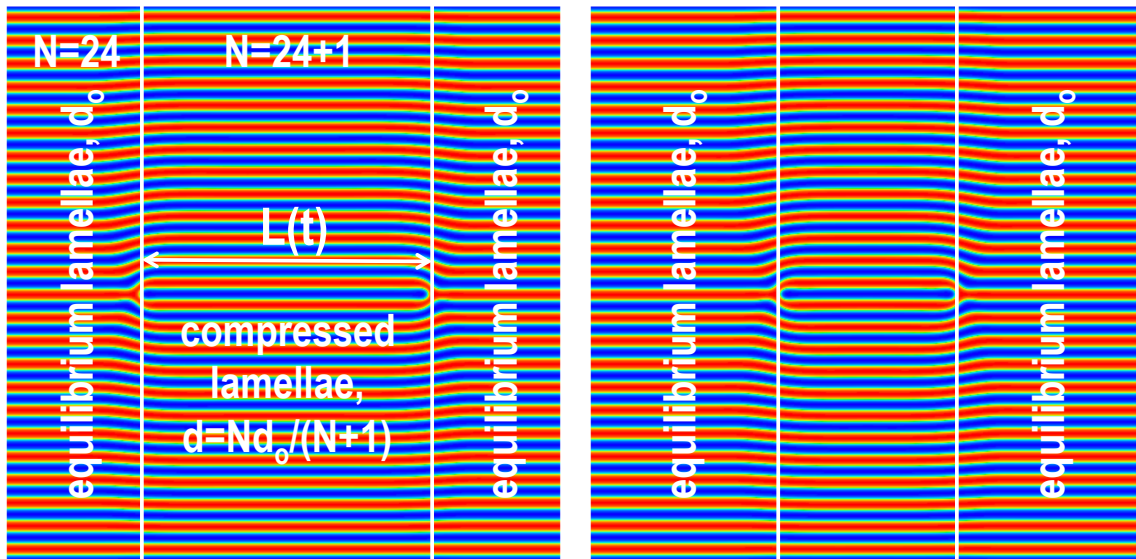
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$$\Delta F_d \sim L \Rightarrow -\frac{\partial \Delta F_d}{\partial L} = \text{const} \quad \text{and} \quad \text{same magnitude for all 3 cases}$$

a) how large is the attractive force?

system: dislocation pair, $\chi N=30$, non-patterned surface, $(24L_0)^2$
 SCFT calculations, $L_0=1.825R_e$, $f=1/2$



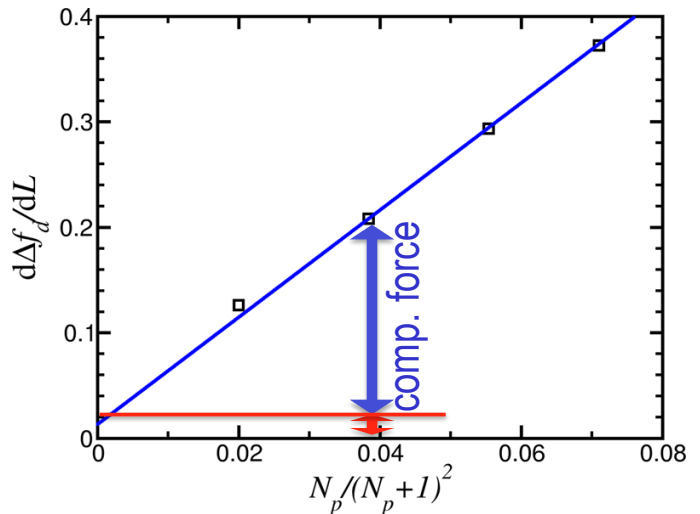
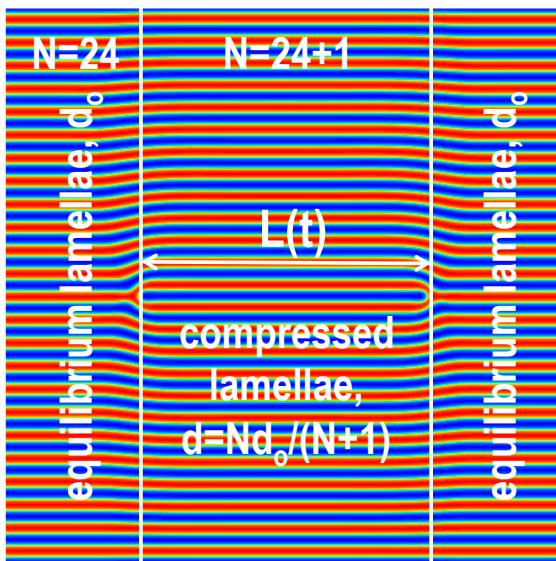
$$\Delta F_d \sim LN(d - d_0)^2 = Ld_0^2 \left(\frac{N}{N+1} - 1 \right)^2 \approx \frac{Ld_0^2}{N}$$

$$\Delta F_d \sim L \Rightarrow -\frac{\partial \Delta F_d}{\partial L} = \text{const}$$

Li, Müller, *Macromolecules* **49**, 6126 (2016)

a) how large is the attractive force?

system: dislocation pair, $\chi N=30$, non-patterned surface, $(24L_0)^2$
 SCFT calculations, $L_0=1.825R_e$, $f=1/2$



$$\Delta f_d = c_1 L \frac{N}{(N+1)^2} + c_2 \ln L + c_3$$

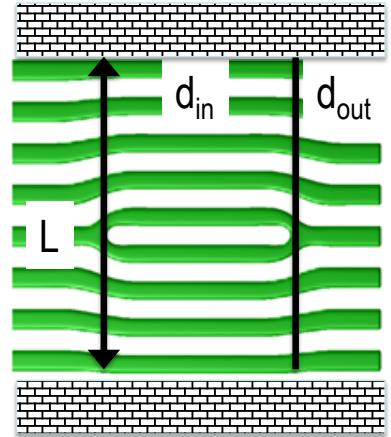
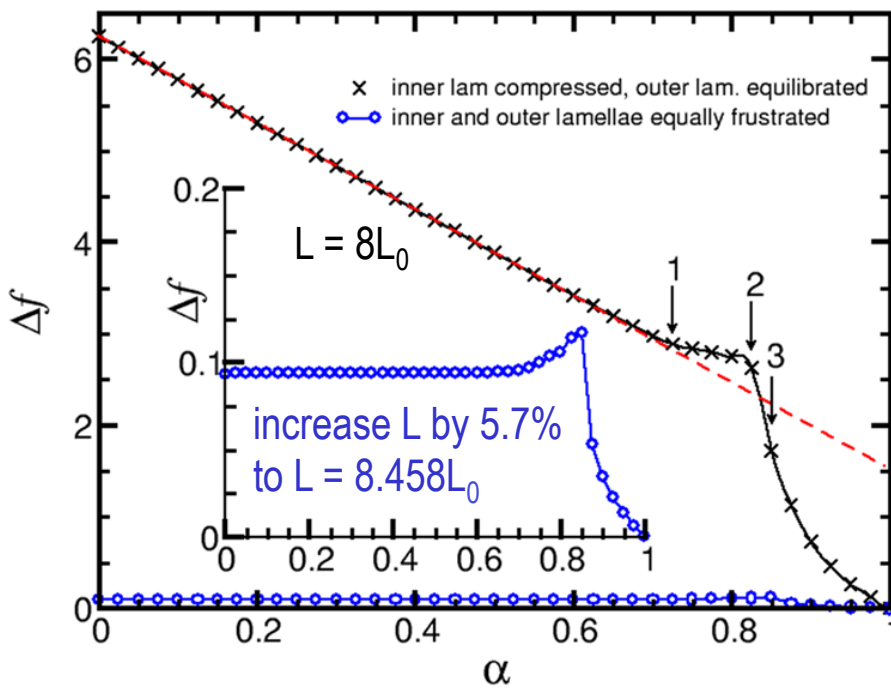
$$\frac{d\Delta f_d}{dL} = c_1 \frac{N}{(N+1)^2} + c_2 \frac{1}{L}$$

$$\Delta F_d \sim L \Rightarrow -\frac{\partial \Delta F_d}{\partial L} = \text{const}$$

➡ compression force dominates over PK force due to finite-size effects

a) how large is the attractive force?

system: dislocation pair, $\chi N=30$, non-patterned surface
 SCFT calculations, $L_0=1.825R_e$, $f=1/2$



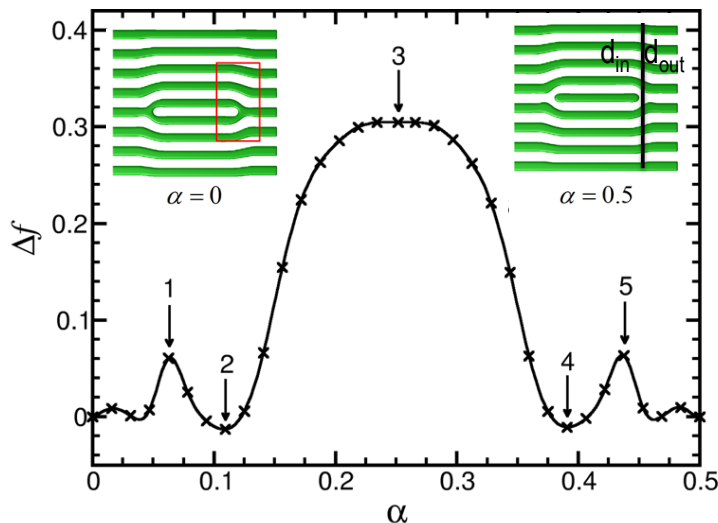
a) $d_{out}=L_0$, $d_{in}<L_0$
 $f(d_{out})<f(d_{in})$

b) $d_{out}>L_0$, $d_{in}<L_0$
 so that $f(d_{out})=f(d_{in})$

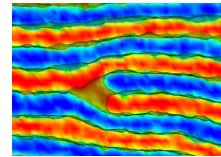
➡ no compression force
 PK very weak
 barrier for annihilation

compression force also dictates dislocation glide

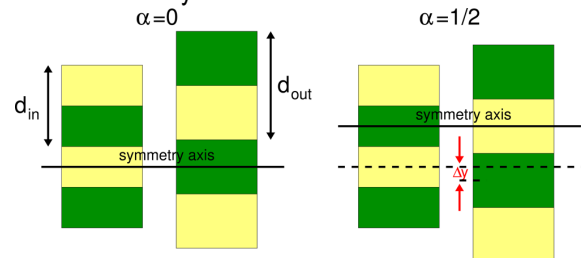
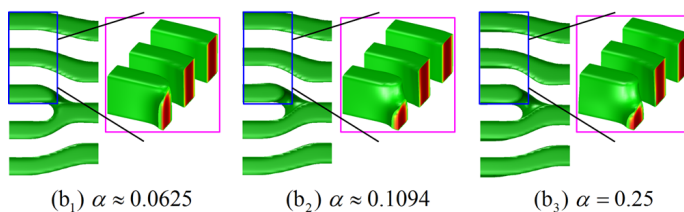
system: dislocation glide by half a period, $\chi N=30$, non-patterned surface
self-consistent field theory (SCFT) calculations / string method F[W]



- states 2 and 4 correspond to metastable half-broken domains



- main barrier of glide arises from subtle shift of domains by $\Delta y \sim 1/L_y$

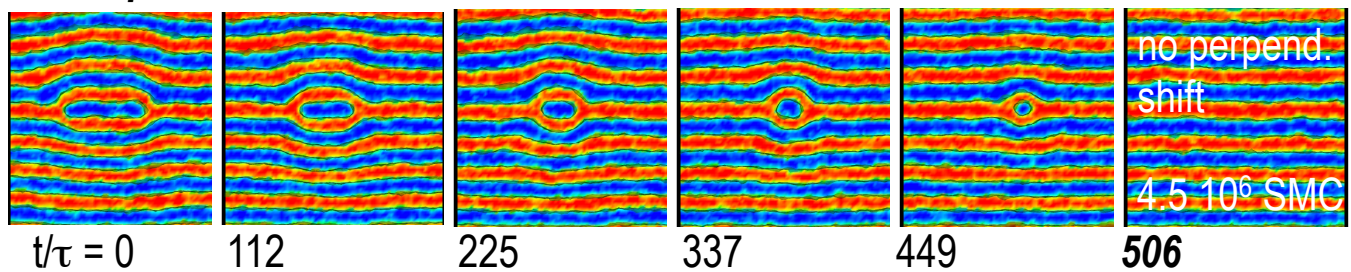


Li, Müller, *Macromolecules* **49**, 6126 (2016)

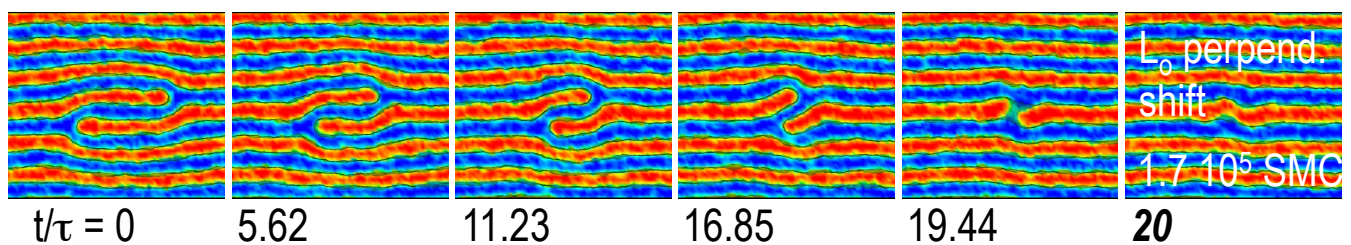
b) how fast does defect move: unconstraint vs evaporation

system: dislocation pair, $\chi N=30$, non-patterned surface
particle simulations using Single-Chain-in-Mean-Field algorithm

evaporation climb

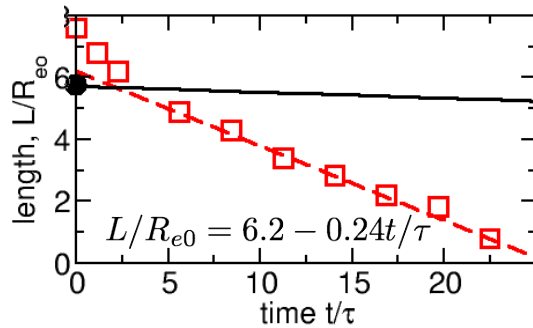


unconstraint climb



➡ both climbs remove defect, but evaporation climb is qualitatively slower

b) how fast does defect move: unconstraint vs evaporation

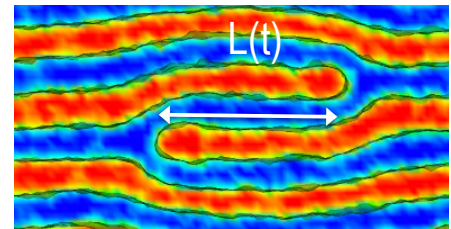


unconstraint climb:

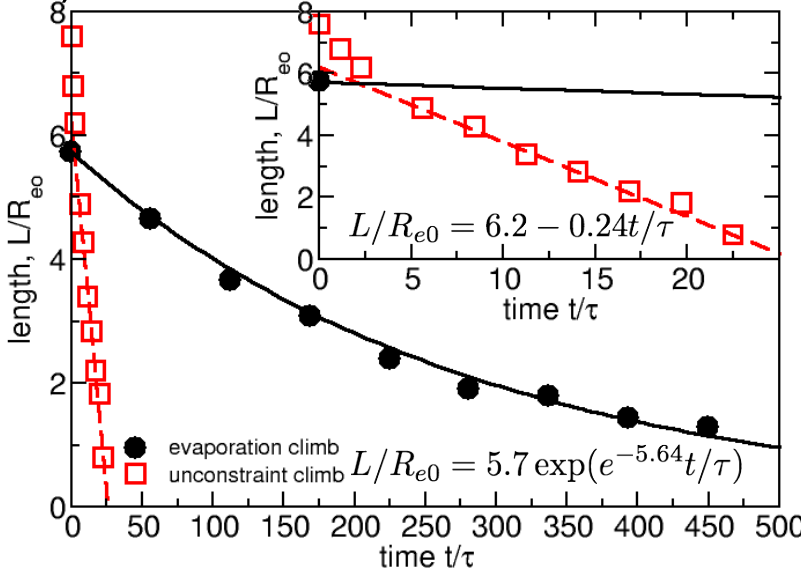
viscous response to force

$$\frac{dL}{dt} \sim -\frac{\partial \Delta F_d}{\partial L}$$

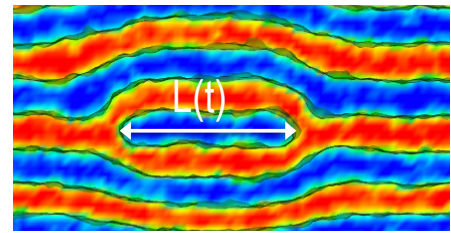
➔ constant velocity,
linear decrease of L



b) how fast does defect move: unconstraint vs evaporation



unconstraint climb:
viscous response to force
 $\frac{dL}{dt} \sim -\frac{\partial \Delta F_d}{\partial L}$
➔ constant velocity,
linear decrease of L



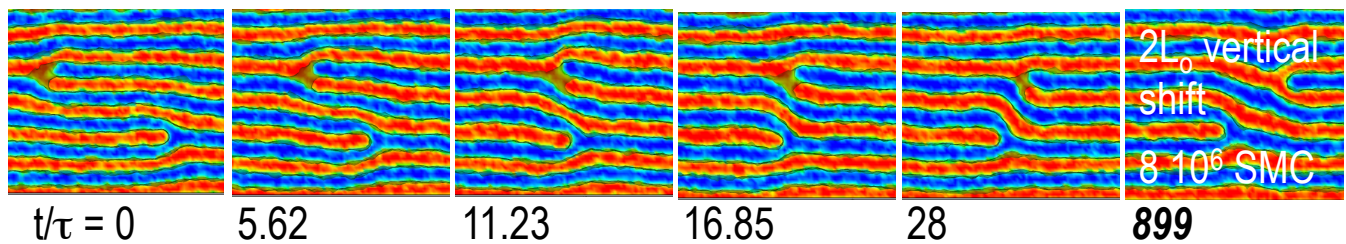
evaporation climb: constant evaporation rate, r , of block from extra lamella

➔ $\frac{\partial \Delta N}{\partial t} \sim -\Delta N \Rightarrow \Delta N \sim L \sim e^{-rt}$ exponential decrease of L

microscopic: blue blocks in extra half lamella “evaporate”, single blocks diffuse through red domain and must overcome free energy barrier $\sim \chi N f k_B T$

macroscopic: $\nabla \mu$ aims at shrinking L, but does not efficiently translate into current, small $\Lambda \sim D \phi_A \phi_B \sim e^{-f \chi N}$ Müller, Daoulas, *Phys. Rev. Lett* **107**, 227801 (2011)

c) does defect motion/collision result in defect annihilation?



stagnation climb: motion arrests in a metastable configuration
here: tight dislocation dipole

defect annihilation is a thermally activated process

➔ **protracted annihilation time** because $\Delta F_d \sim \Delta F_b \sim k_B T \sqrt{N}$

questions:

- what is the microscopic mechanism of defect annihilation?
- what are the concomitant activation free energies (barriers)?

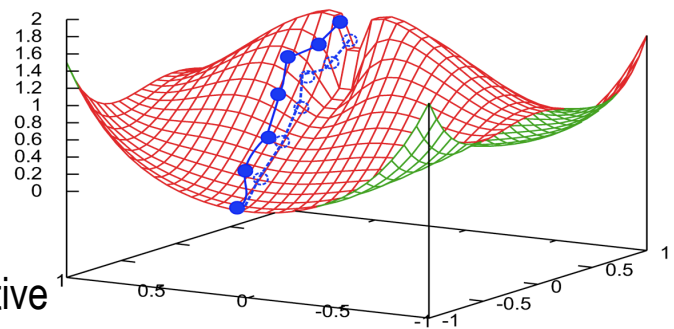
➔ study **Minimum Free-Energy Path (MFEP)** by string method

Li, Nealey, de Pablo, Müller, *Phys. Rev. Lett.* **113**, 168301 (2014)

on-the-fly string method and improved string method

describe transformation path by a string of morphologies $m_s(\mathbf{r})$ with contour variable $0 \leq s \leq 1$

minimum free-energy path (MFEP) is defined by condition that the derivative perpendicular to the path vanishes



improved string method:

E, Ren, Vanden-Eijnden, *J. Chem. Phys.* **126**, 164103 (2007)

1. evolve each morphology $m_s(\mathbf{r})$ as to minimize the free energy

$$\frac{\delta F_c[m_c]}{\delta m_c(\mathbf{r})} = \lambda k_B T [m_c(\mathbf{r}) - \langle \hat{m}(\mathbf{r}) \rangle_c] \xrightarrow{\lambda \rightarrow \infty} \mu(\mathbf{r}|m_c) \quad \Delta m_s(\mathbf{r}) = -\mu(\mathbf{r}|m_s) \Delta$$

2. re-parameterize the string to equal distance Δs (pointwise 3rd order spline)

SCFT: Cheng, Lin, E, Zhang, Shi, *Phys. Rev. Lett.* **104**, 148301 (2010); Ting, Appelö, Wang, *Phys. Rev. Lett.* **106**, 168101 (2011); Li, Nealey, de Pablo, Müller, *Phys. Rev. Lett.* **113**, 168301 (2014)

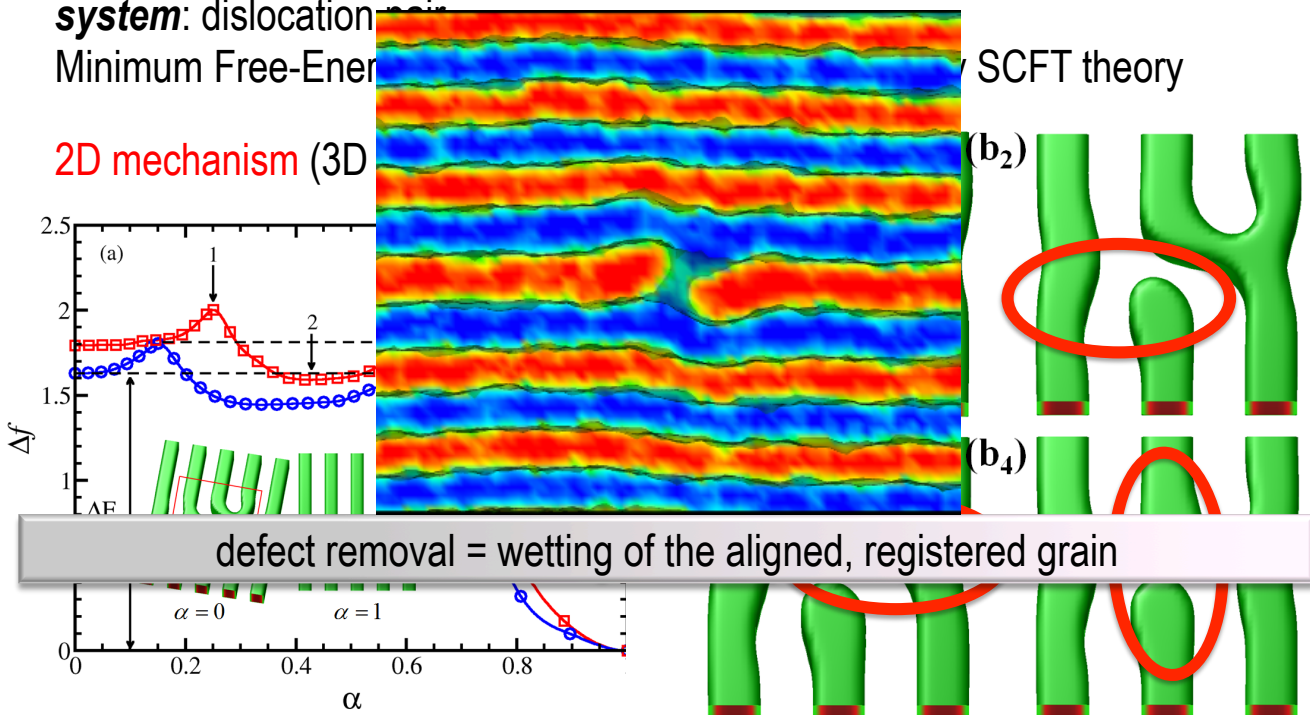
particle simulations: Maragliano, Vanden-Eijnden. *Chem. Phys. Lett.*, **446**, 182 (2007); Miller, Vanden-Eijnden, Chandler, *PNAS* **104**, 14559 (2007); Müller, Smirnova, Marelli, Fuhrmans, Shi, *Phys. Rev. Lett.* **108**, 228103 (2012); Müller, Sun, *Phys. Rev. Lett.* **111**, 267801 (2013); Hur, Thapar, Ramirez-Hernandez, Khaira, Segal-Peretz, Rincon-Delgadillo, Li, Müller, Nealey, de Pablo, *PNAS* **112**, 14144 (2015)

interface models: Giacomello, Meloni, Müller, Casciola, *J. Chem. Phys.* **142**, 104701 (2015), Ryham, Klotz, Yao, Cohen, *Biophys. J.* **110**, 1110 (2016)

defect annihilation by *lateral* interface motion (2D)

system: dislocation pair
Minimum Free-Energy

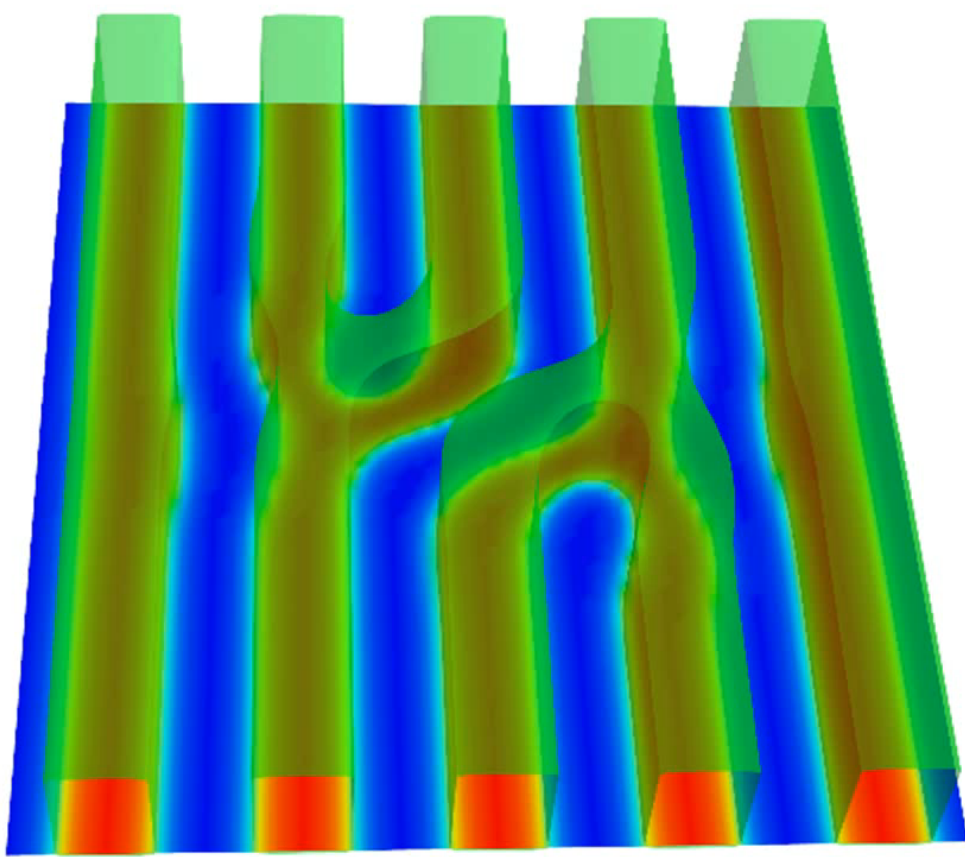
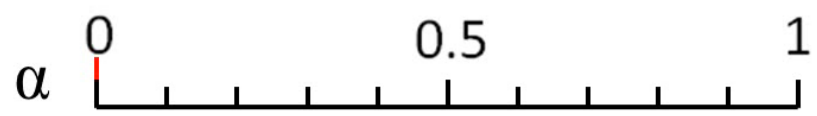
2D mechanism (3D)



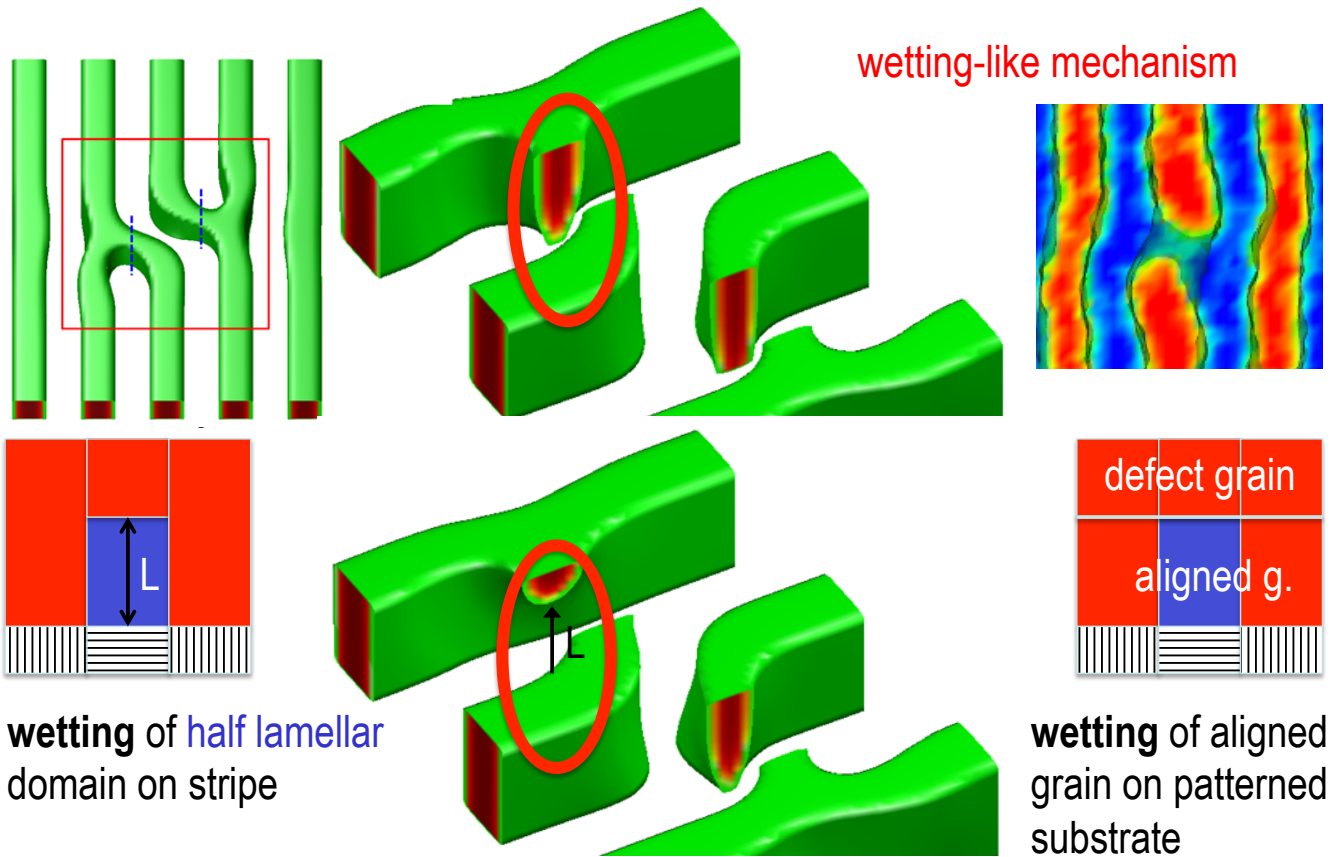
without guiding pattern, $\Delta N=0$

sequential breaking of connections

2D calculation for graphoepitaxy see [Takahashi, et al, Macromolecules 45, 6253 \(2012\)](#)

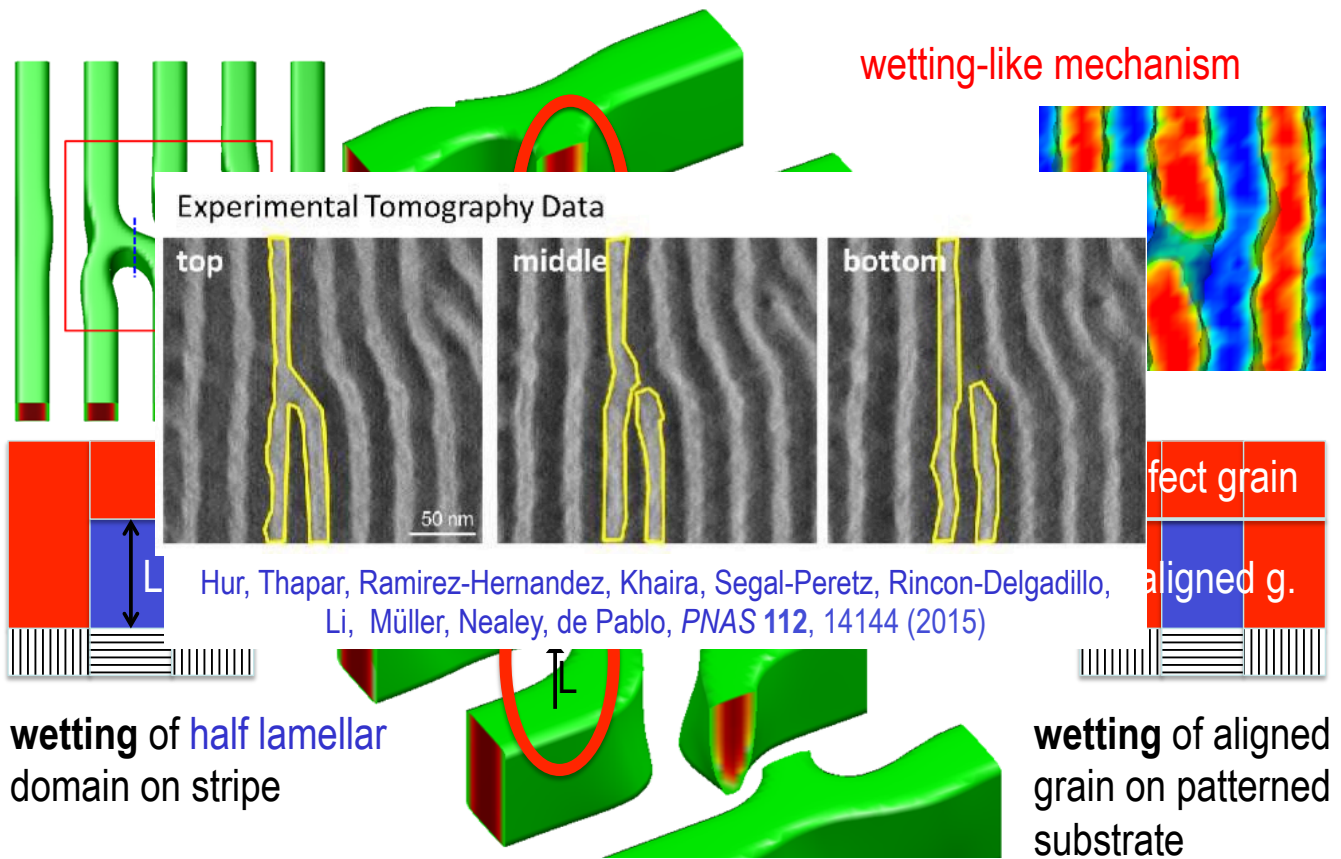


defect annihilation by *perpendicular* interface motion



Li, Nealey, de Pablo, Müller, *Phys. Rev. Lett.* **113**, 168301 (2014)

defect annihilation by *perpendicular* interface motion



Hur, Thapar, Ramirez-Hernandez, Khaira, Segal-Peretz, Rincon-Delgadillo, Li, Müller, Nealey, de Pablo, *PNAS* **112**, 14144 (2015)

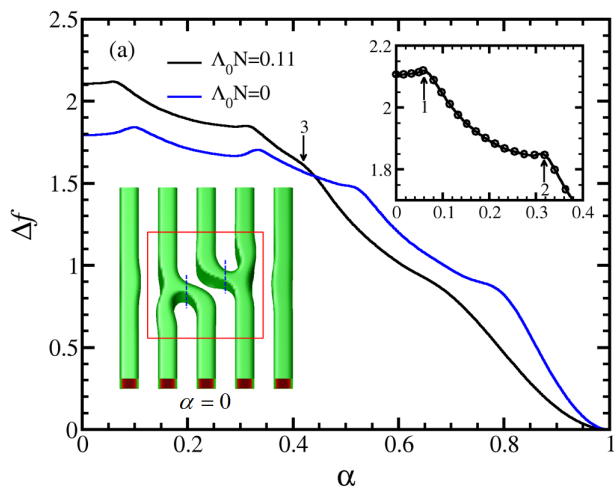
Li, Nealey, de Pablo, Müller, *Phys. Rev. Lett.* **113**, 168301 (2014)

defect annihilation by *perpendicular* interface motion

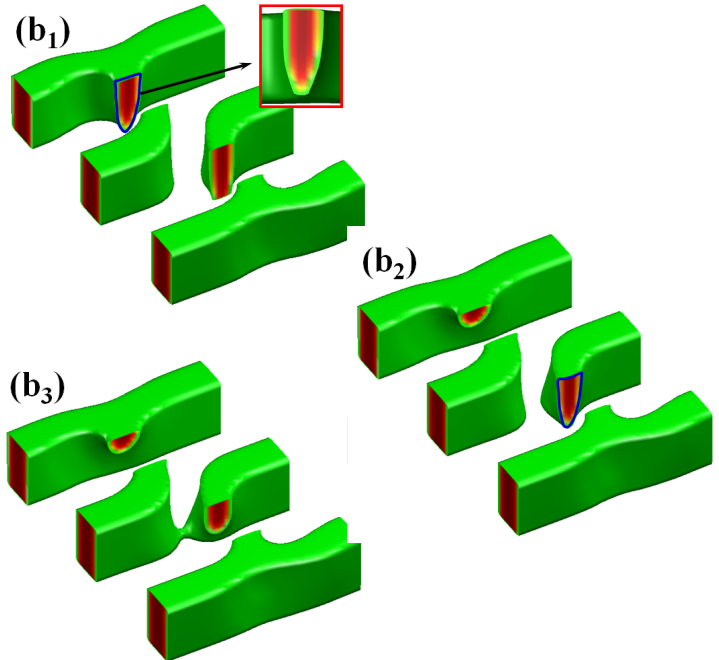
system: dislocation pair

Minimum Free-Energy Path (MFEP) of $F[W]$ obtained by SCFT theory

wetting-like mechanism



without and with guiding pattern

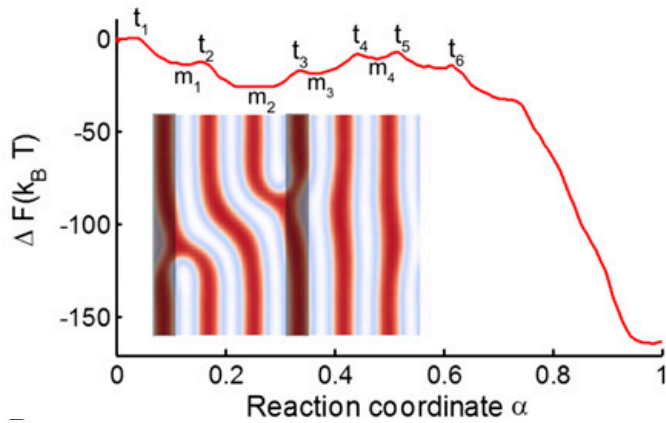


sequential breaking of connections

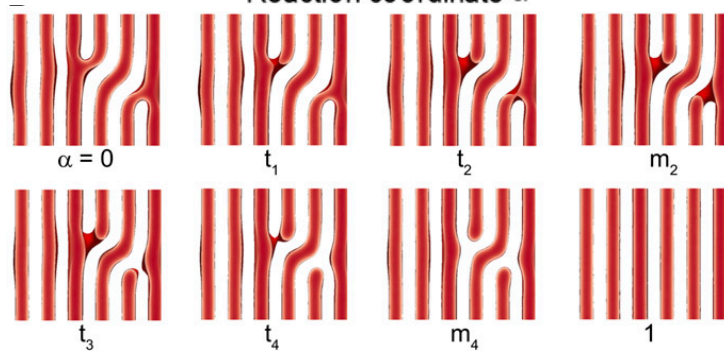
Li, Nealey, de Pablo, Müller, *Phys. Rev. Lett.* **113**, 168301 (2014)

defect annihilation for larger “impact parameter”

system: dislocation pair, $\chi N=20$, 3×density multiplication, 3 L_0 perp. shift
 Minimum Free-Energy Path (MFEP) obtained by particle simulation



- defect annihilation involves dislocation glide and breaking of connections via a wetting-like mechanism
 ─▶ multiple barriers
- pathway and barrier depends on relative position of defects cores with respect to guiding pattern

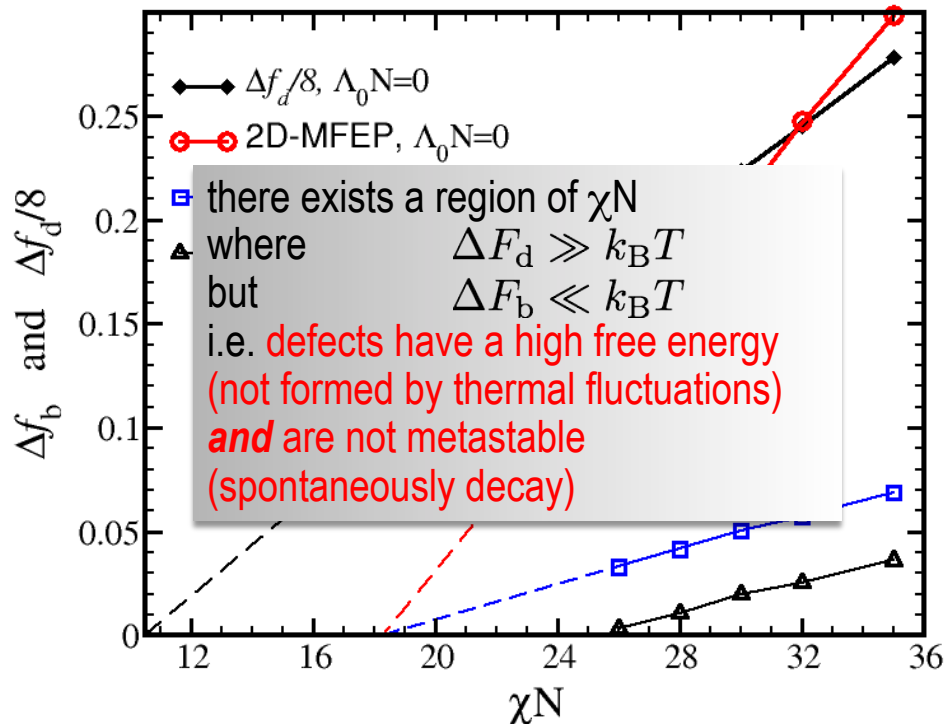


Hur, Thapar, Ramírez-Hernández,
 Khaira, Segal-Peretz, Rincon-Delgadillo,
 Li, Müller, Nealey, de Pablo,
 PNAS 112 14144 (2015)

defect removal is enhanced close to ODT

system: dislocation pair

Minimum Free-Energy Path (MFEP) of $F[W]$ obtained by SCFT theory



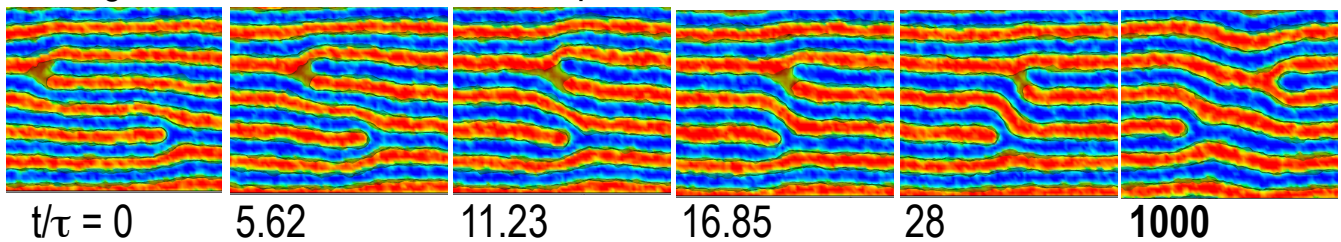
Li, Nealey, de Pablo, Müller, *Phys. Rev. Lett.* **113**, 168301 (2014)

process-directed self-assembly: defect removal at low χN

system: dislocation pair

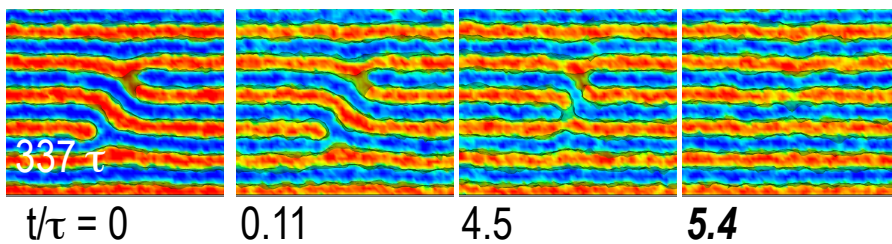
particle simulations using Single-Chain-in-Mean-Field algorithm

stagnation climb – metastable dipole

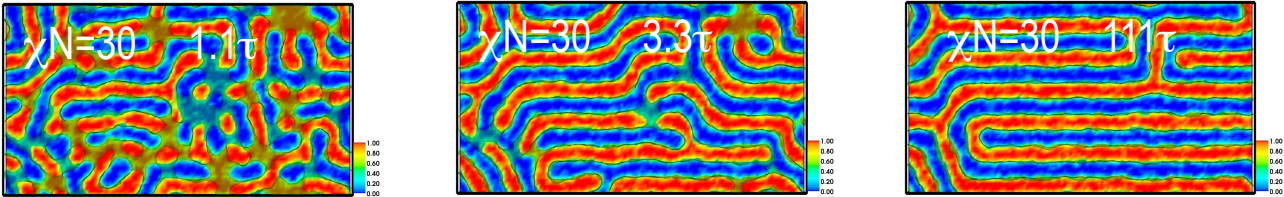


observation at $\chi N=30$: distance between dislocations decreases in time
collide and form a metastable tight dislocation dipole

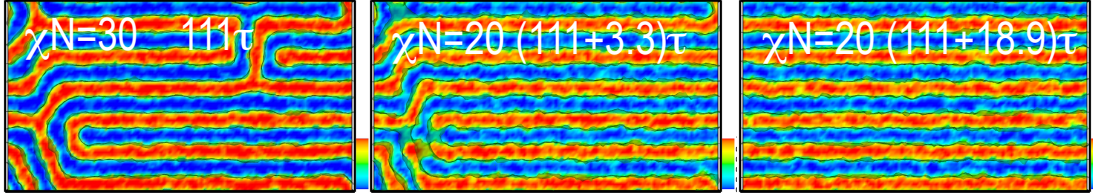
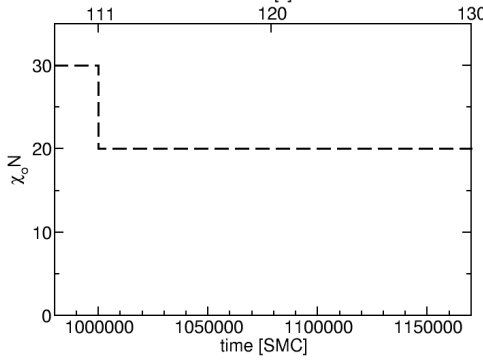
quench from $\chi N=30$ to 20 renders tight dislocation dipole unstable



process-directed self-assembly: defect removal at low χN



L/S pattern – no density multiplication
 eliminate well-formed metastable
 disclination defects ($111\tau @ \chi N = 30$)
 by reducing $\chi N = 30 \rightarrow 20$



➔ defect are eliminated
 but time scale is longer than ordering from disordered state at $\chi N = 20$

summary

- excess free-energy of defects is prohibitive $\Delta F \sim O(100k_B T)$:
defects will not spontaneously form but arise in course of structure formation
 - local smectic-A geometry controls defect motion and collision
deviation from Peach-Koehler force due to boundary/finite-size effects
 - **defect removal fast at intermediate segregations, $\chi N_* \approx 18$**
process window increases with preference of guiding pattern
- process-directed self-assembly**: tailor free energy landscape of self-assembly by temporal control of thermodynamic state variable, e.g., χN or solvent

W.H. Li, U. Welling, J.C. Orozco Rey, S.M. Hur, P.F. Nealey, J.J. de Pablo

